

# Development of a dedicated beam forming system for material and bioscience research with high intensity, small field electron beam of LILLYPUT 3 accelerator at Wrocław Technology Park



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Wrocław, Poland



# Abstract

The LILLYPUT 3 electron accelerator designed and manufactured at National Centre for Nuclear Research in Swierk, Poland (NCBJ) is the principal instrument of The Nondestructive Testing Laboratory at Wroclaw Technology Park.

The accelerator delivers 6 and 9 MeV electron beams. In a standard configuration the electron beam is converted into X-ray beam in a water cooled tungsten target. The primary use of the accelerator is nondestructive testing including R&D of novel techniques for industrial and medical imaging.

In addition, the high intensity electron beam can be directly extracted for a broad range of applications including material and bioscience research. For those applications a specialized beam forming system has been designed at NCBJ.

The purpose of this system is to deliver as high intensity electron beam as possible, while keeping beam flatness within 10% on a 7x7 sq. cm field in the distance of 40 cm from the beam exit window. Two alternative solutions were taken into consideration, one involving beam scanning and second based on passive beam forming with flattening foil. While it seemed that the highest beam intensity can be achieved by beam scanning, the in-depth study of the system performance revealed that, under available resources, the realistically achievable beam intensity is going to be comparable in both solutions. Taking into account simplicity and considerably lower costs of the passive beam forming system this solution was adopted. Optimization of the final system design was performed with a dedicated Geant4-based application created specifically for this purpose. The system is being currently fabricated at NCBJ.

In this paper the methodology, results as well as tools involved in the design of the specialized beam forming system will be presented.



## Introduction and Motivation

- The LILLYPUT-3 accelerator at the Nondestructive Testing Laboratory (NTL) at Wrocław Technology Park
- High-dose irradiation under cryogenic conditions (objectives, requirements, constraints, etc.)
- Electron beam forming – active (scanning) VS passive (scattering)

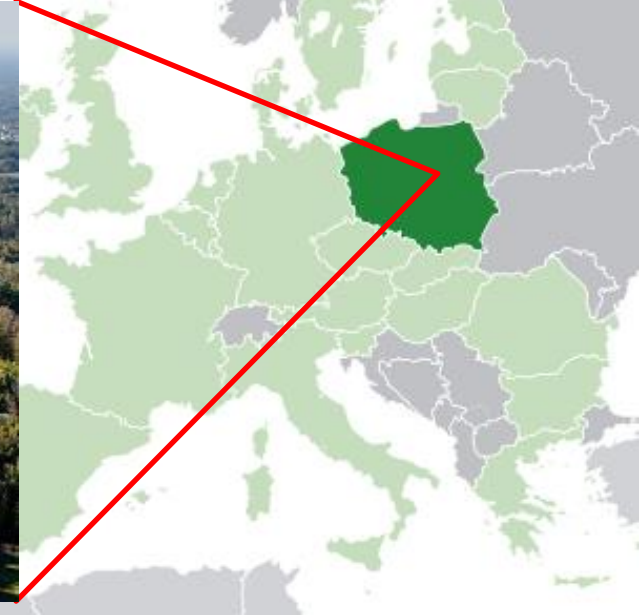
## Design of the system

- Beam scanning – reality check
- Physics principles of dual foil system operation
- Simple analytical model of electron fluence
- Impact of helium filled applicator – motivation for development of a MC model
- Geant4 model and tools for automatized design
- System optimization
- Calculation of expected dose rate

## Conclusions and outlook



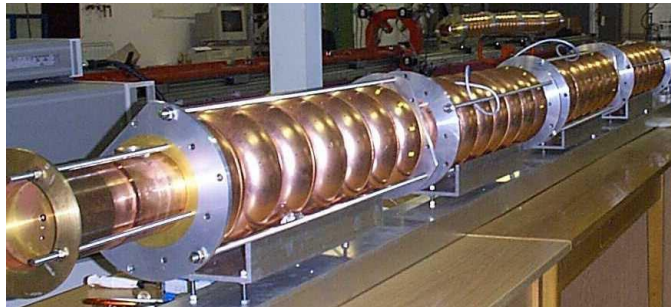
# National Centre for Nuclear Research, Swierk, Poland



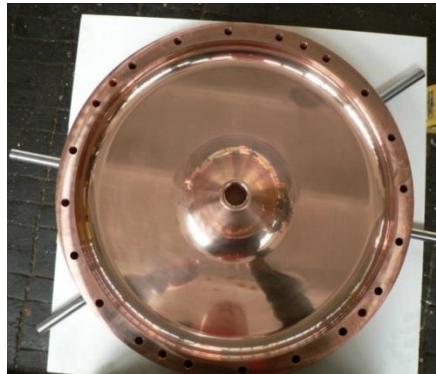
- ✓ The largest research institute in Poland (1000+ employees)
- ✓ Broad scope of fundamental and applied research
  - Nuclear physics (including reactor physics)
  - High energy physics (in collaboration with CERN and others)
  - Plasma physics
  - Material science
  - Free-electron lasers (in collaboration with XFEL)
- ✓ Tradition of development and production of radiopharmaceuticals and medical equipment, including linear accelerators



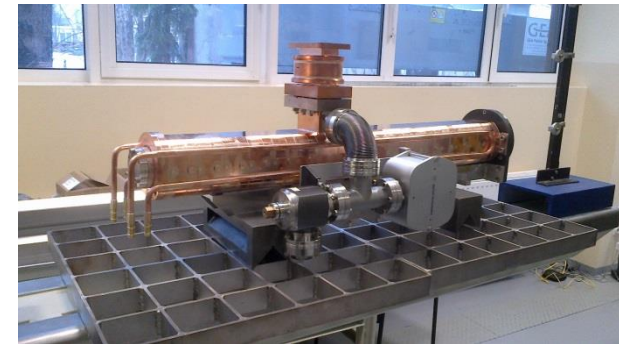
# NCBJ and electron LINACs for science, industry, medicine



Prototype cavities 1.3 GHz for Tesla-FEL at DESY



cavity for LINAC4@CERN



Prototype for mobile IOERT



Mobile linac for industrial radiography



Assembly of a medical linac

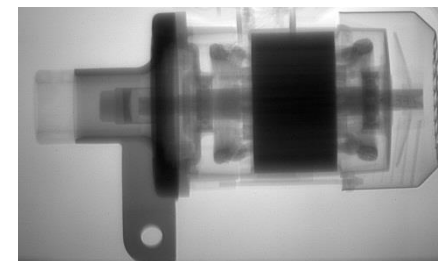
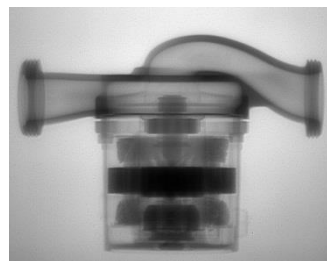
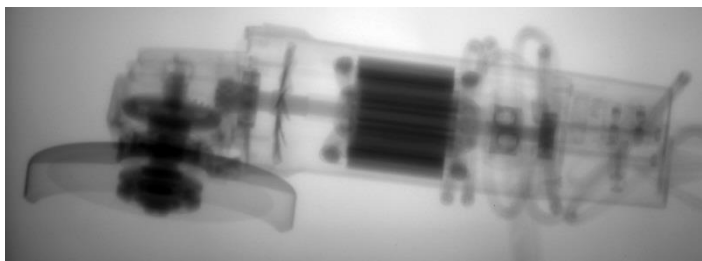


# The LILLYPUT-3 accelerator at The Nondestructive Testing Laboratory at Wrocław Technology Park



## Standard radiographic configuration

- 6 and 9 MV X-ray beams
- Maximum dose rate 20 Gy/min
- Maximum field size  $\Phi 500\text{mm}$  @ 1m (adjustable with automatized jaw collimators)
- Digital imaging
- Automatized object table





# High-dose electron beam irradiation at NTL

## Primary motivation

- Tests of radiation hardness of insulators (tens of MGy absorbed dose, cryogenic conditions)
- R&D in sterilization of polymer based medical products (tens of kGy)
- Research in polymer structure modifications (tens of kGy)

## Perspectives, R&D opportunities

- Effects of irradiation on the structure of high temperature superconductors
- Effects of irradiation on the response time of electronic circuits
- Enhancement of optical properties of gemstones
- Coating hardening and regeneration
- Purification of exhaust gases from combustion of fossil fuels
- Food preservation





# High-dose electron beam irradiation under cryogenic conditions at NTL

## Primary motivation

- Tests of radiation hardness of insulators (tens of MGy absorbed dose, cryogenic conditions)

## Objectives

- Irradiation of samples under cryogenic conditions (LN<sub>2</sub>)
- Maximize dose rate (~ few tens of kGy/min). Total absorbed dose in the range of few tens of MGy.

## Requirements

- Well flattened beam (i.e. homogenous dose distribution over sample area)
- Relatively small field size (~ $\Phi$ 80mm). Square samples ~60x60 mm

## Approach towards system adaptation

- 9 MeV electron beam (extracted directly in a non-standard configuration)
- Shortest possible source to sample distance (SSD ~400 mm)
- Least possible disruption of the existing system







# Least possible disruption of the existing system...



RF power supply (3 GHz)

Radiation head



electron linac



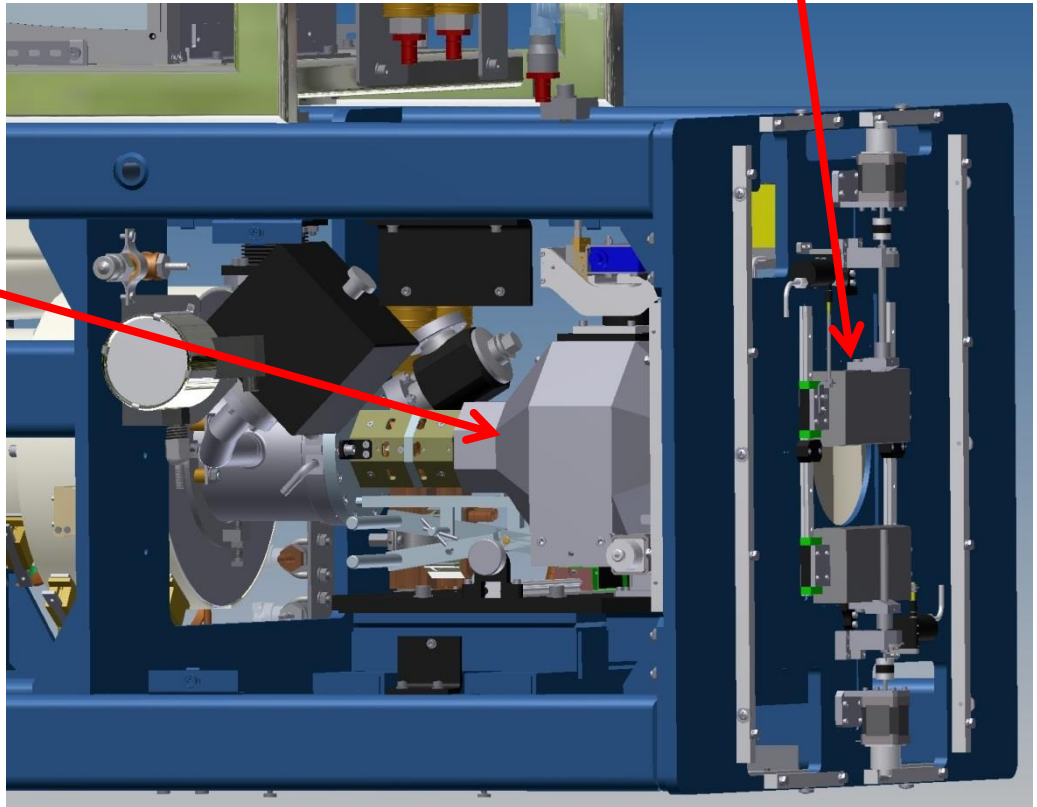
# Least possible disruption of the existing system...



## Radiation head in standard configuration

Movable X-ray jaw collimators  
(two pairs, X and Y axis)

Primary X-ray collimator



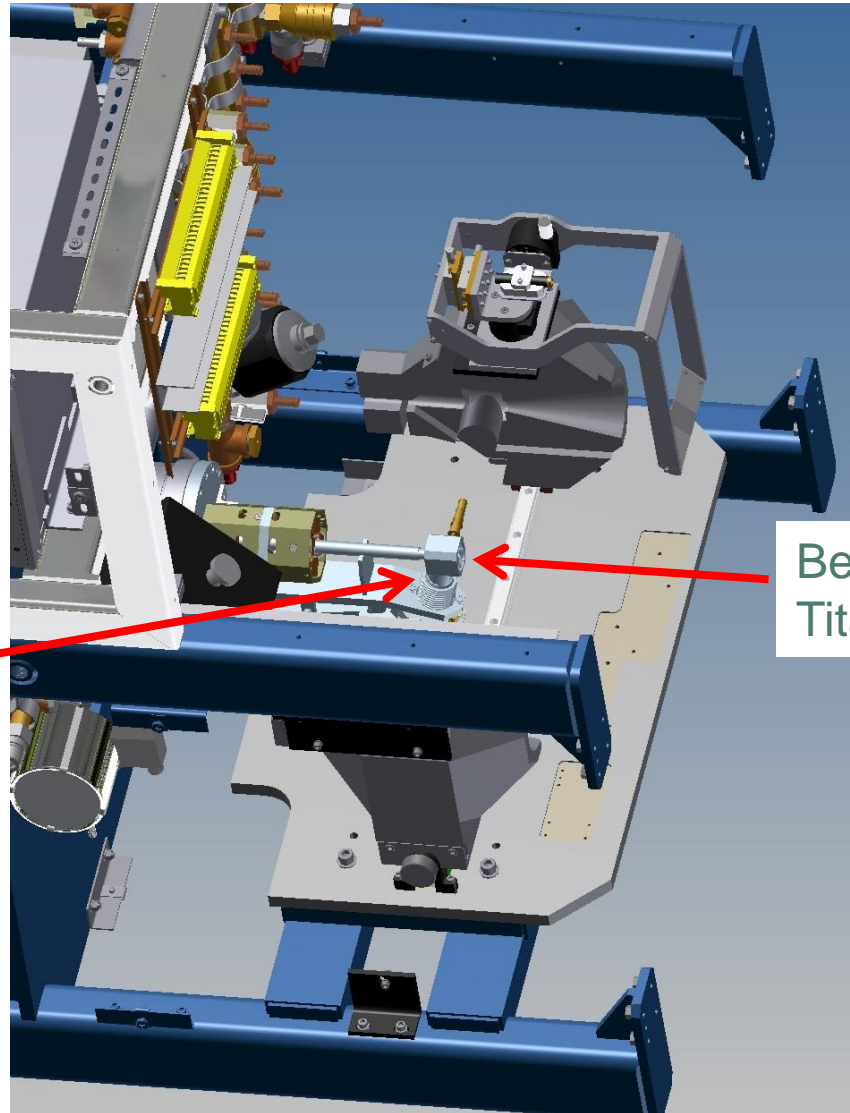
Modular construction allows for reasonably simple removal of modules



# Least possible disruption of the existing system...



## Radiation head dismantled



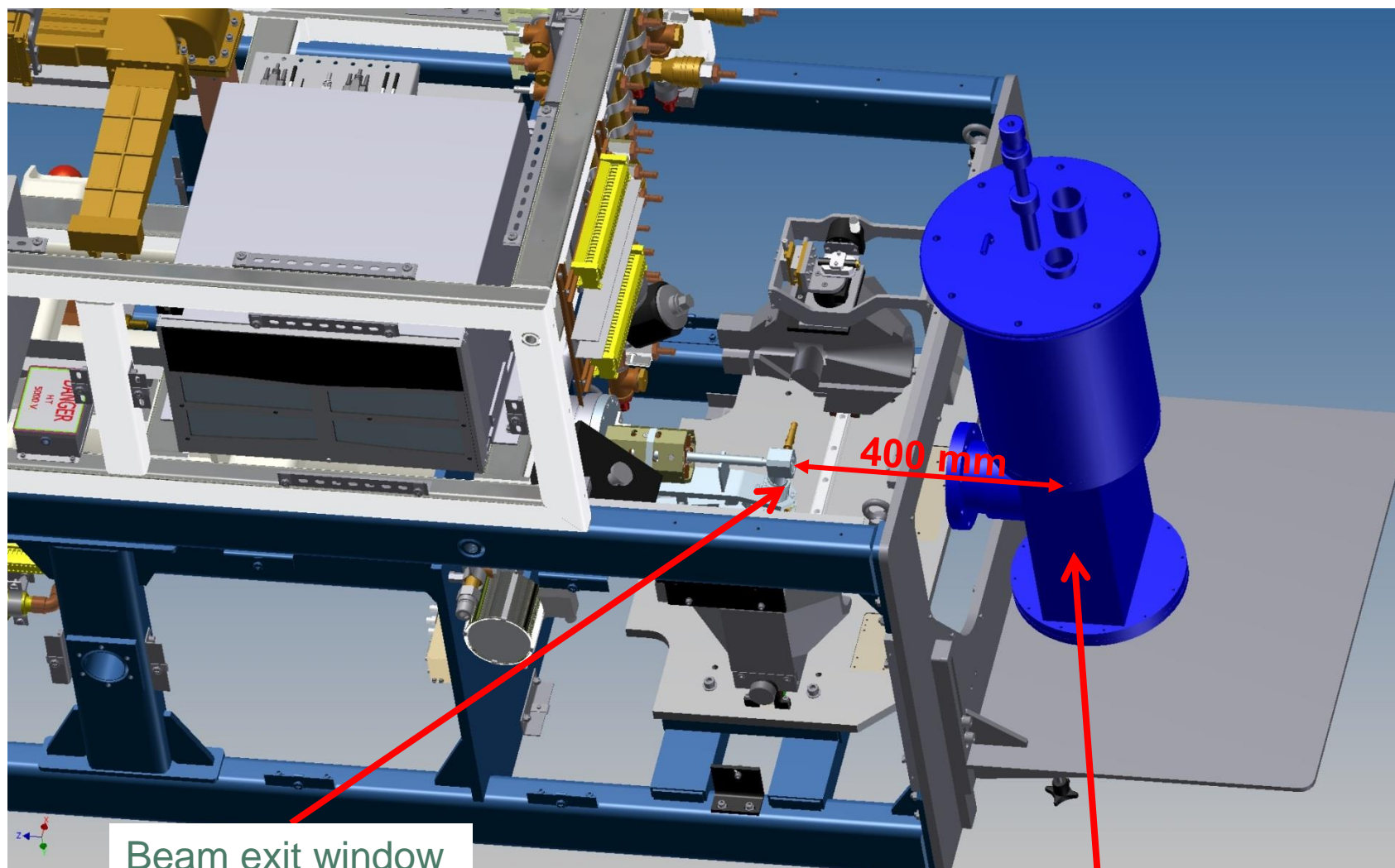
Beam exit window  
Titanium, 0.05 mm

Target chamber

X-ray production targets  
can be moved in and out  
of beam path (in vacuum)



# Least possible disruption of the existing system...

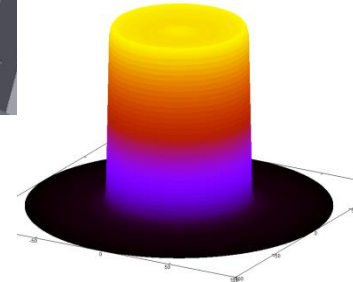
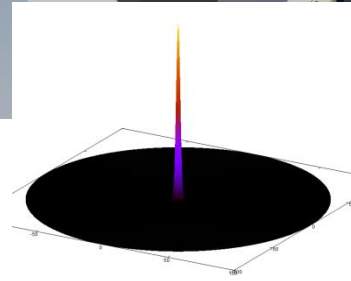
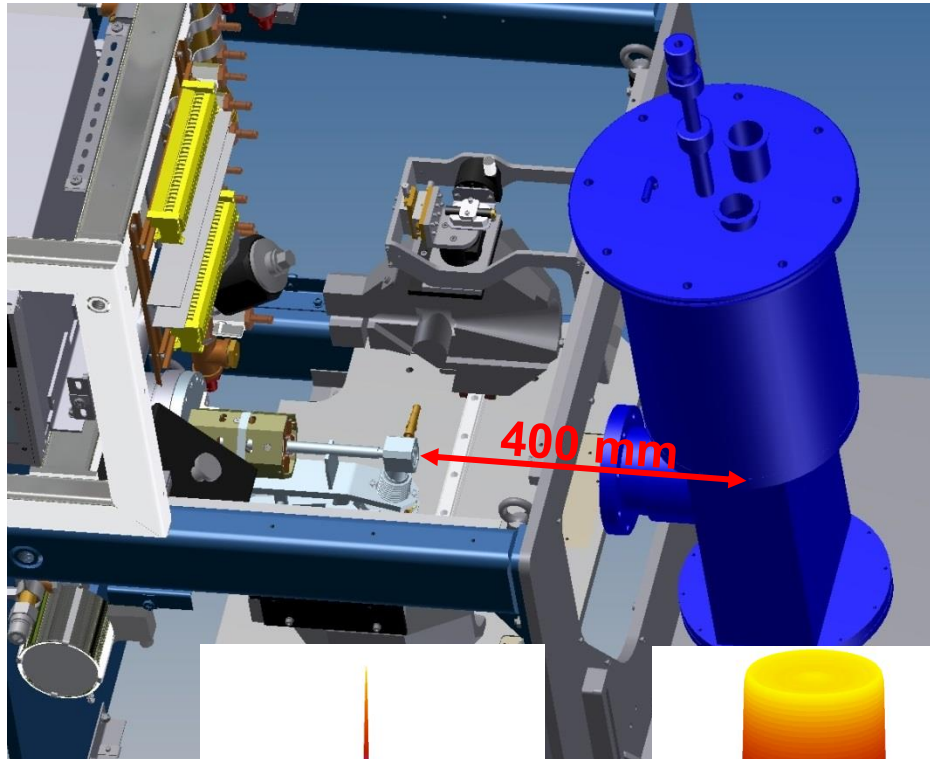


Beam exit window  
Titanium, 0.05 mm

LN<sub>2</sub> cryostat  
(holds irradiated samples)



# Electron beam forming system – what is it good for?



Beam fluence at the exit window

- „pencil beam”
- very narrow (FWHM ~3 mm)
- extremely nonuniform

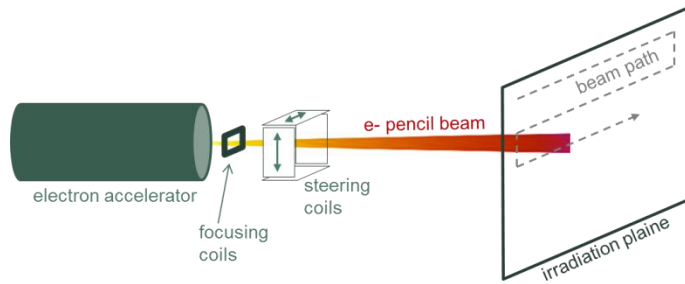
Desired beam fluence at sample location

- uniform over large area ( $\Phi \sim 8$  cm)



# Electron beam forming – active VS passive

active = beam scanning



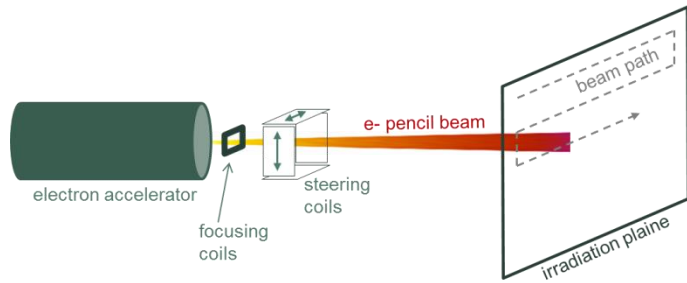
Common applications: sterilization, industrial material processing (e.g. polymer cross linking), modern hadron therapy

- 👍 **High efficiency (→ high dose rate)**
- 👎 Relatively complex system (especially for 2D scanning)
- 👎 Nontrivial to achieve uniform dose distribution
- 👎 Difficult to control beam uniformity



# Electron beam forming – active VS passive

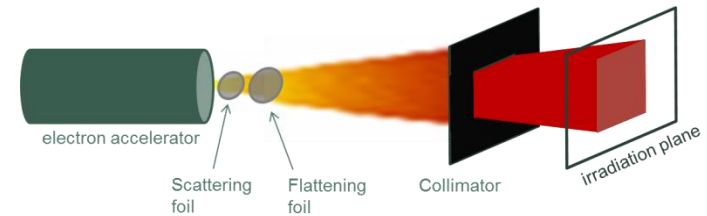
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passive = beam scattering and collimation



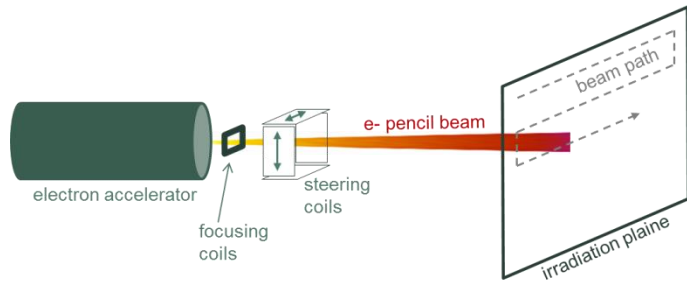
Common applications: electron beam therapy (also previous generation of proton therapy)

- 👍 Uniform beam distribution
- 👍 Simple, reliable
- 👎 **Significantly less efficient**



# Electron beam forming – active VS passive

active = beam scanning



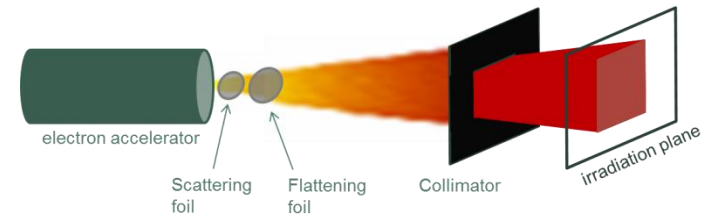
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- 👍 **High efficiency (→ high dose rate)**
- 👎 Relatively complex system (especially for 2D scanning)
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- 👎 Difficult to control beam uniformity



In this application, efficiency is all that matters

passive = beam scattering and collimation



Common applications: electron beam therapy (also previous generation of proton therapy)

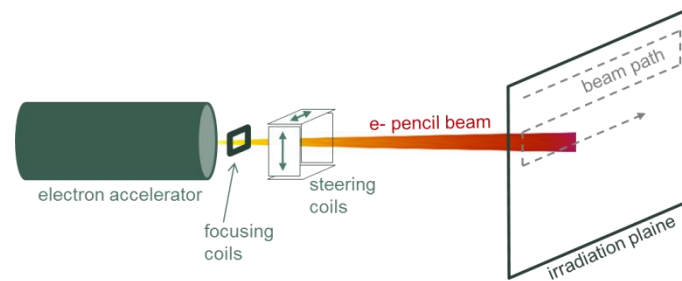
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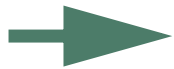


# Electron beam scanning – reality check



e- beam  
9 MeV

400 mm

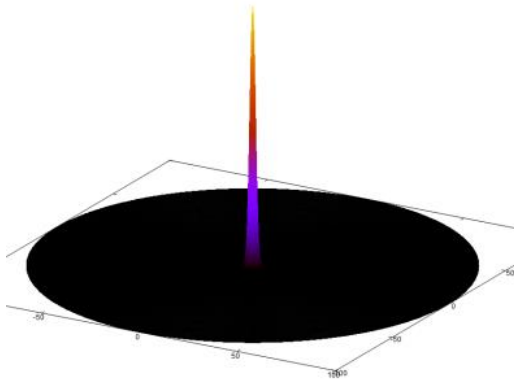


Air  
10 mm

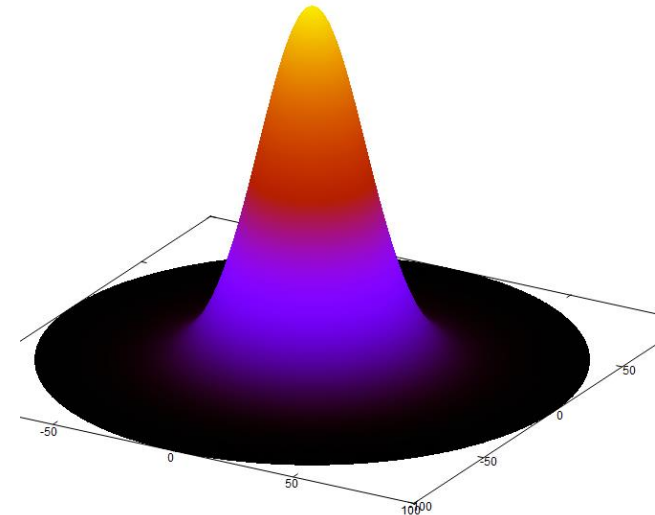
Vacuum

50  $\mu\text{m}$  Ti  
Exit window

50  $\mu\text{m}$  Ti  
Vacuum chamber entrance window



FWHM 3 mm

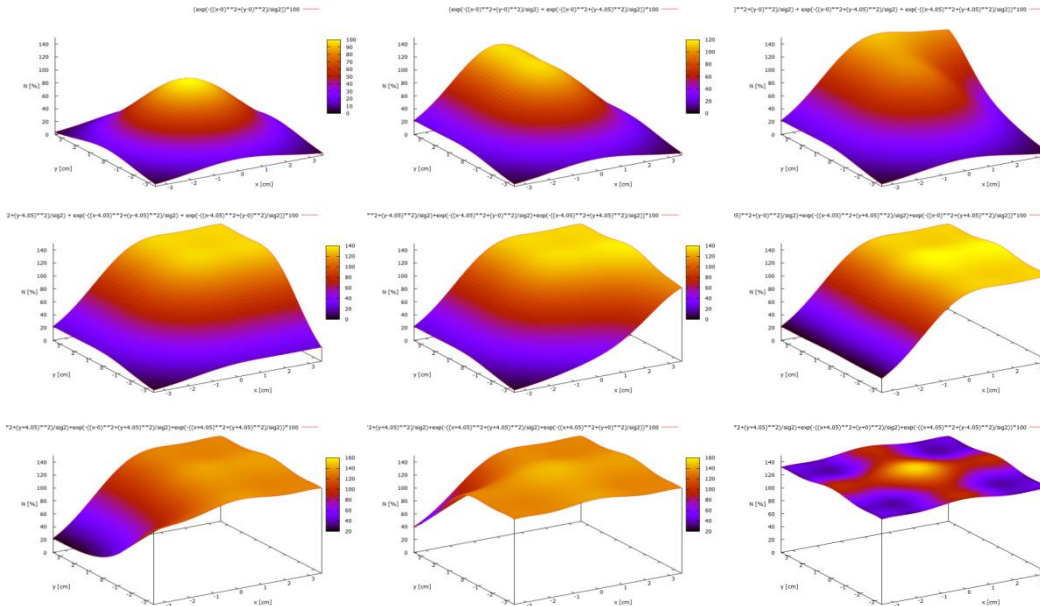
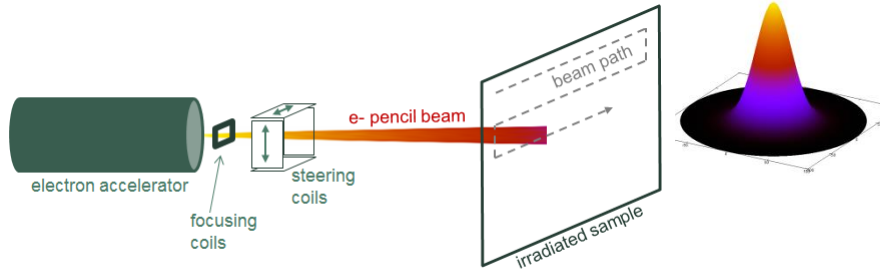


FWHM 45 mm



# Electron beam scanning – reality check

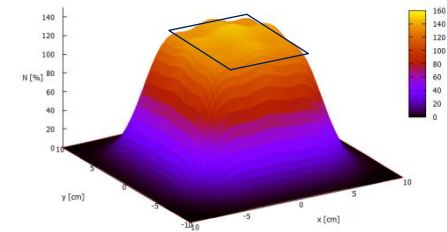
Simple model of beam scanning on a 7x7 cm<sup>2</sup> field with a beam of FWHM = 45mm



Decent uniformity\* (~12%)

but

Efficiency ~ 30 % (or 70% of the beam ends up outside of the field)

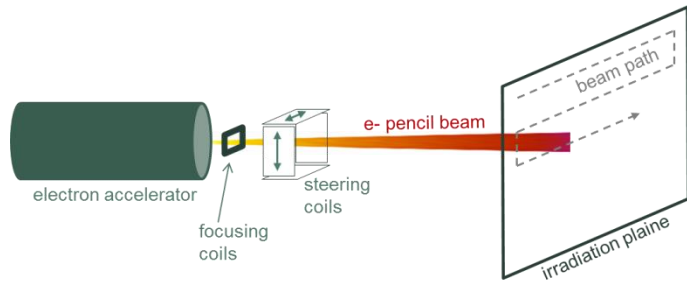


\*) Flatness (uniformity) of electron beam fluence calculated as  $flatness = \left( \frac{\Phi_{max}}{\Phi_{min}} - 1 \right) \cdot 100\%$







# Electron beam forming – active VS passive

active = beam scanning

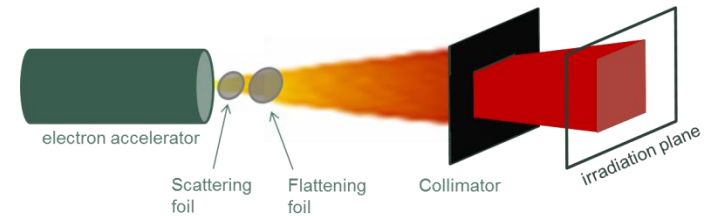


Common applications: sterilization, industrial material processing (e.g. polymer cross linking), hadron therapy




-  ~~High efficiency (→ high dose rate)~~
-  Relatively complex system (especially for 2D scanning)
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passive = beam scattering and collimation



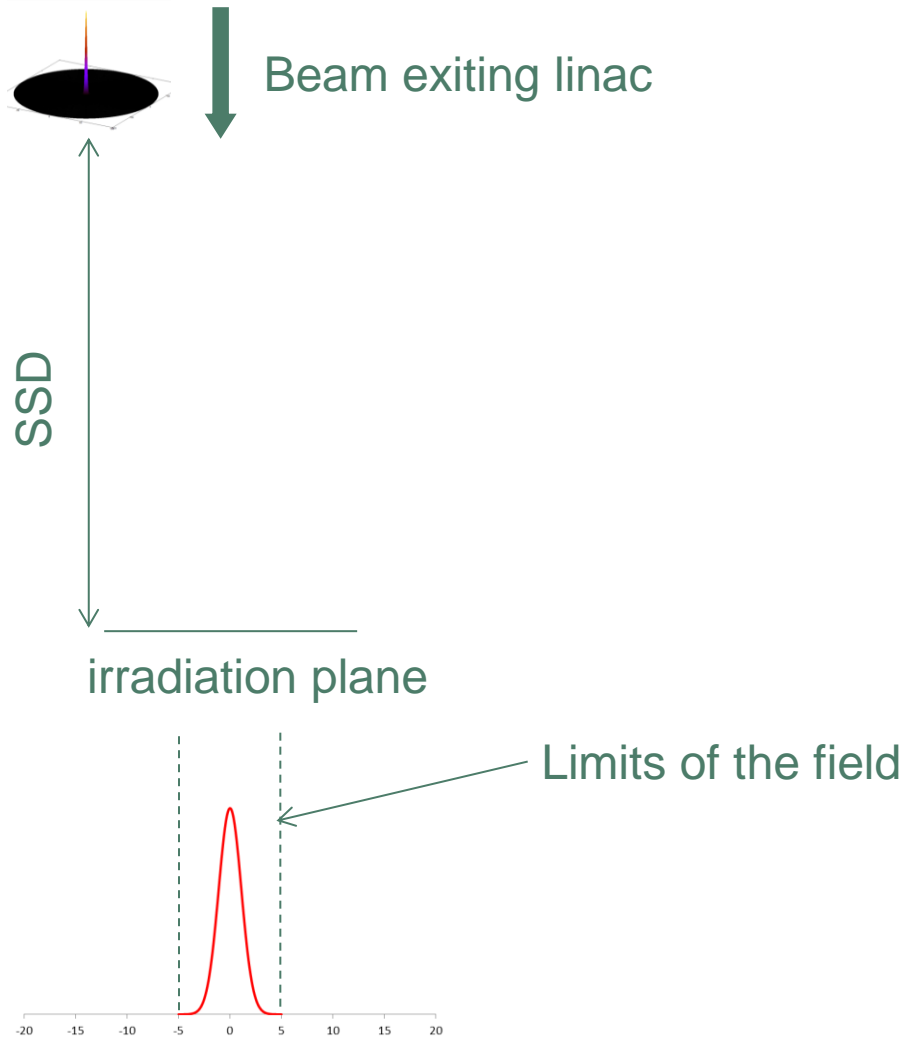
Common applications: electron beam therapy (also previous generation of proton therapy)

-  Uniform beam distribution
-  Simple, reliable
-  ~~Significantly less efficient~~



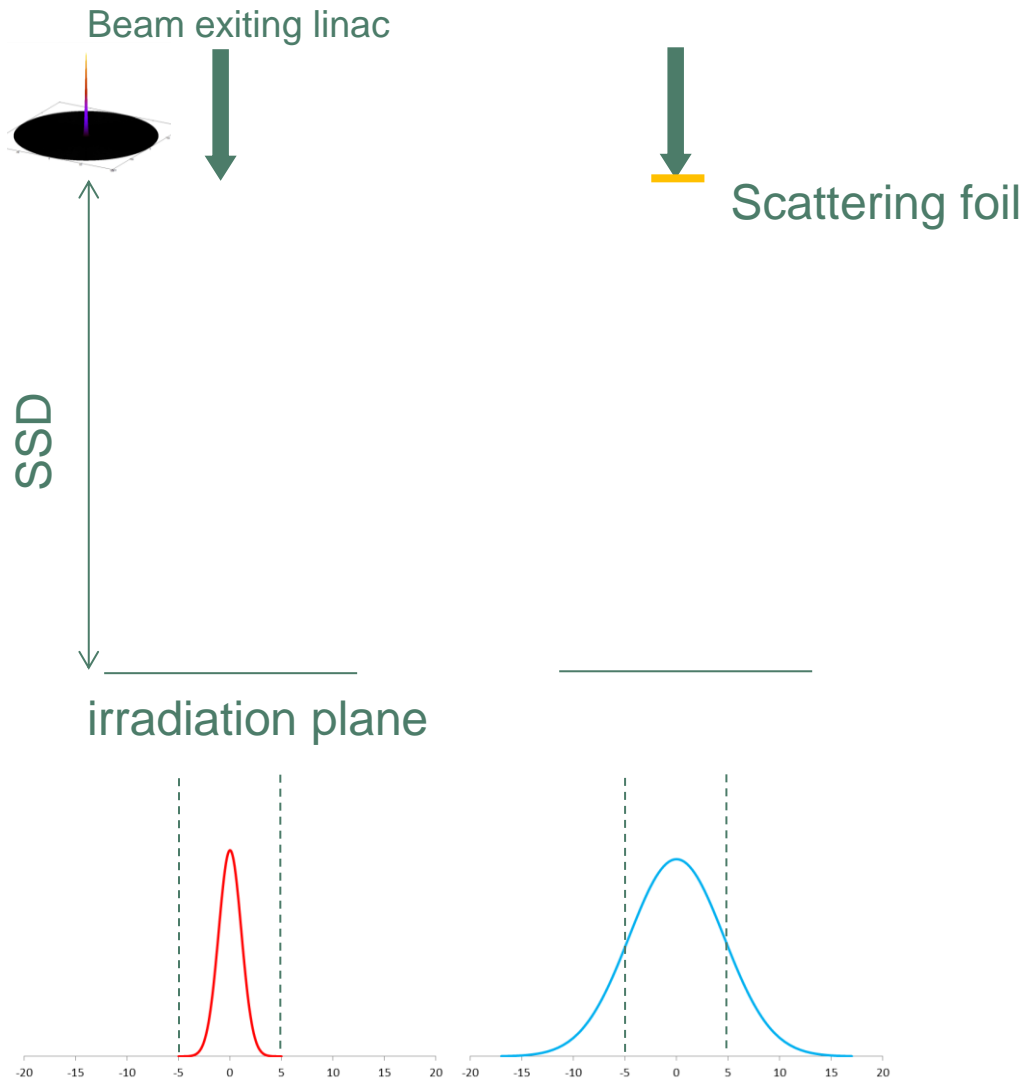


# The principle of dual-foil system



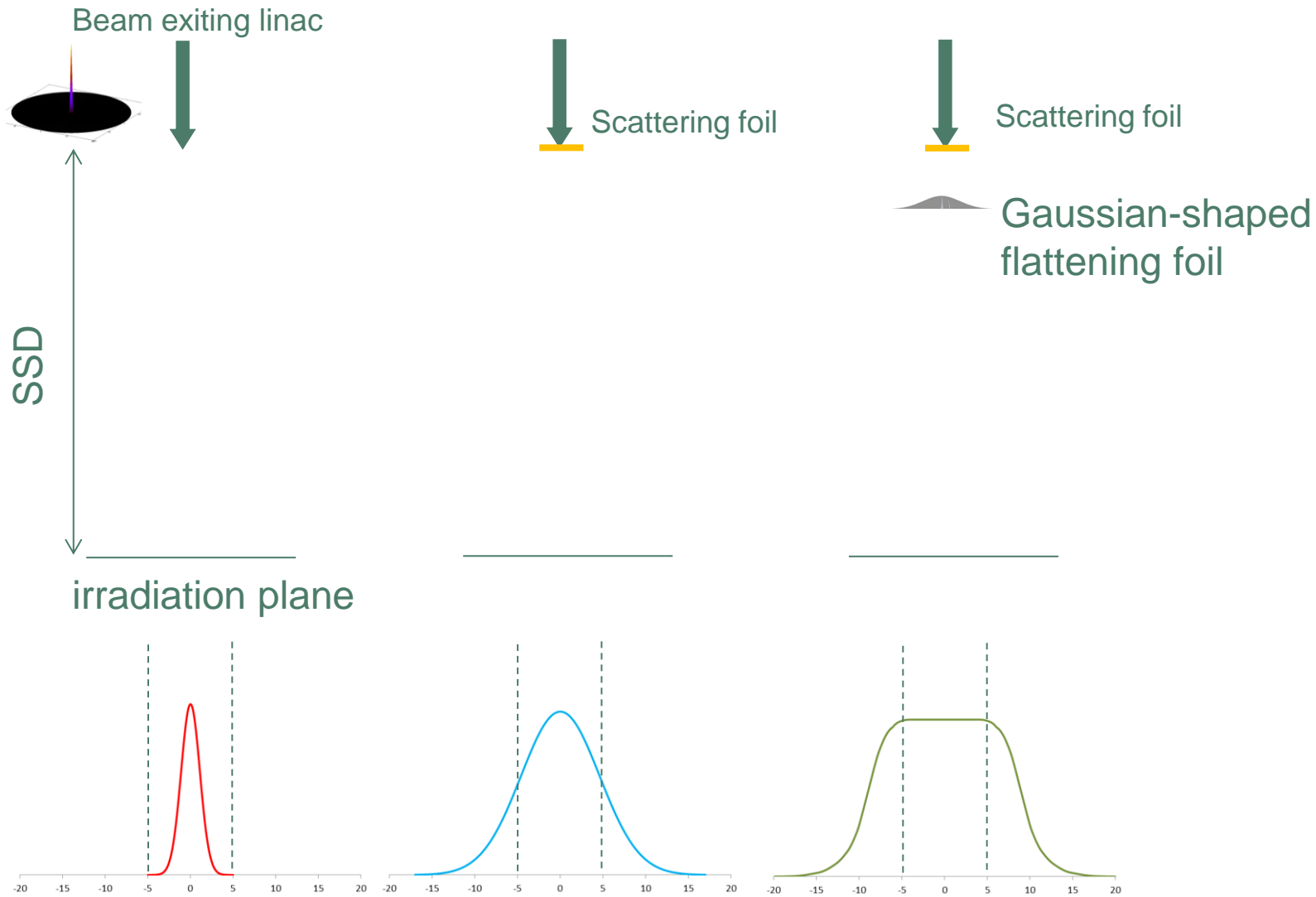


# The principle of dual-foil system



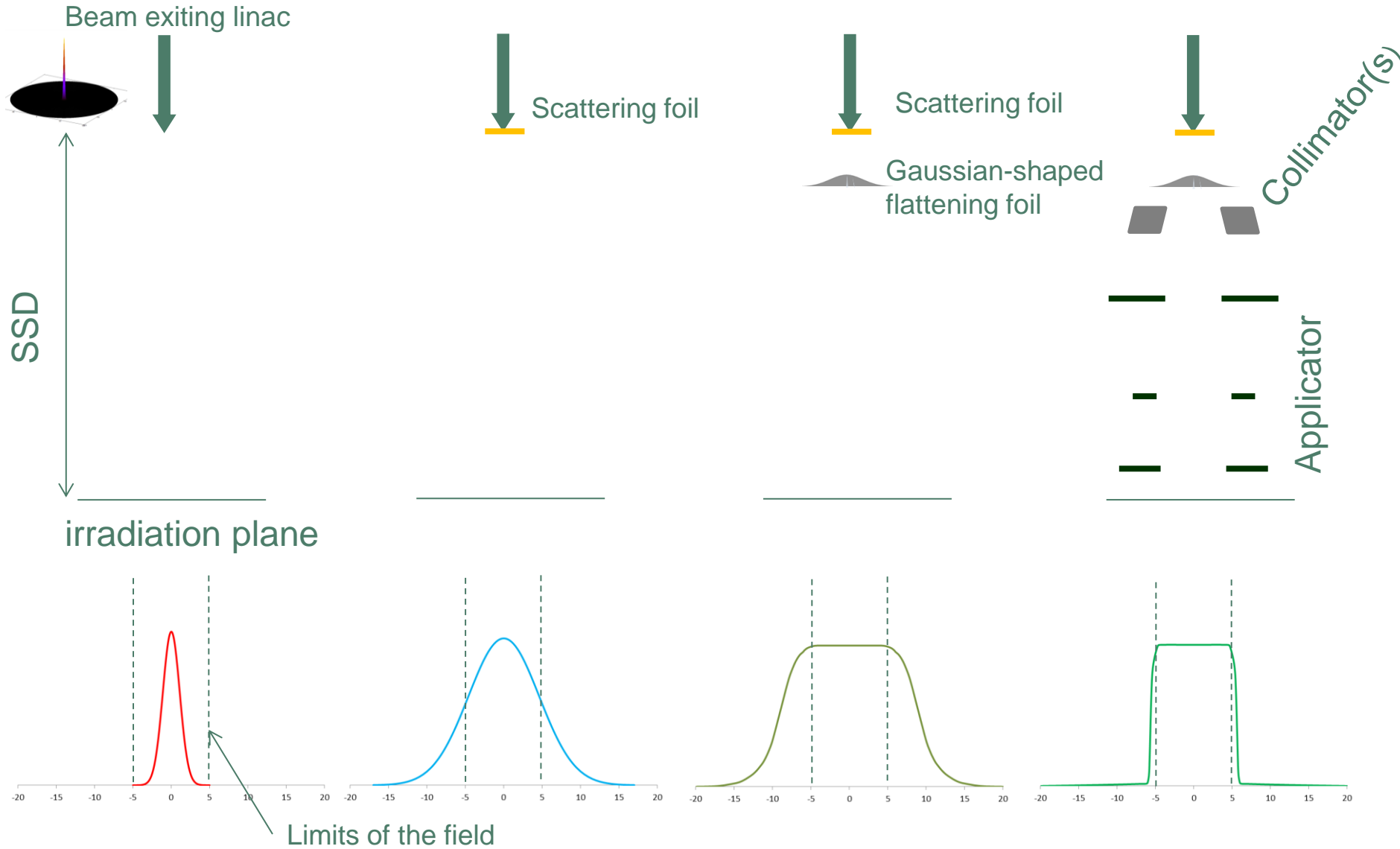


# The principle of dual-foil system





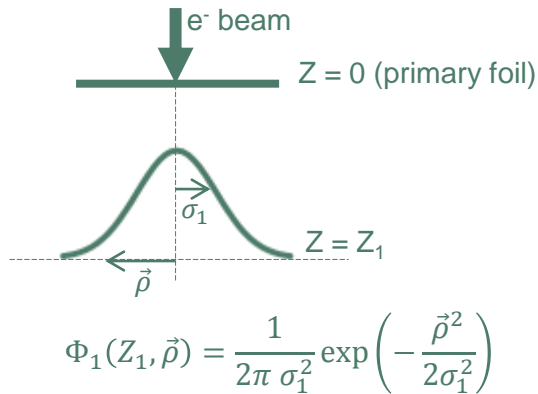
# The principle of dual-foil system



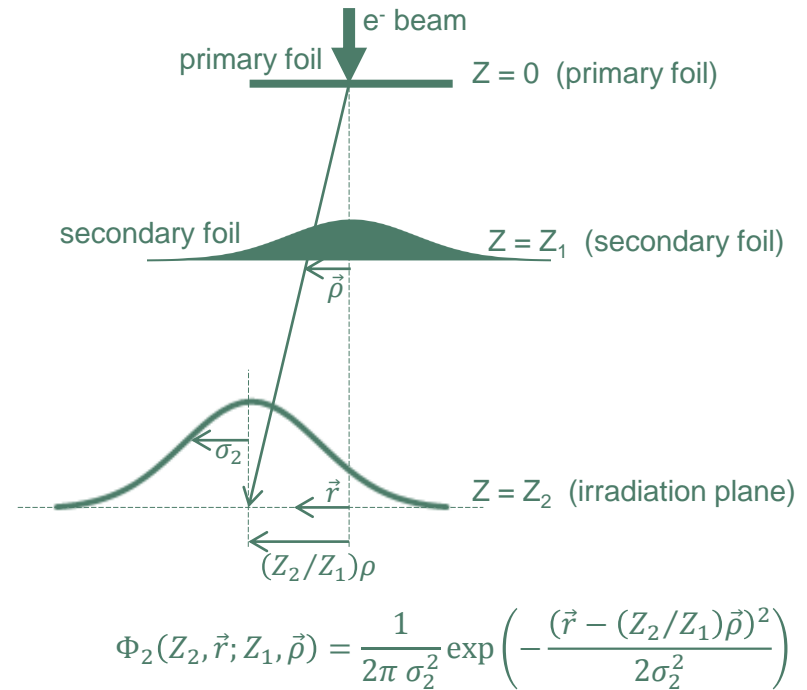


# Calculation of electron fluence – simple model

Electron fluence at the position of the secondary foil due to scattering in the primary foil and in the air between foils



Component of the fluence at the irradiation plane due to a beamlet originating from rho at the second foil



Fluence at point  $\vec{r}$  at the irradiation plane  $Z_2$  is a convolution of  $\Phi_1$  and  $\Phi_2$ :

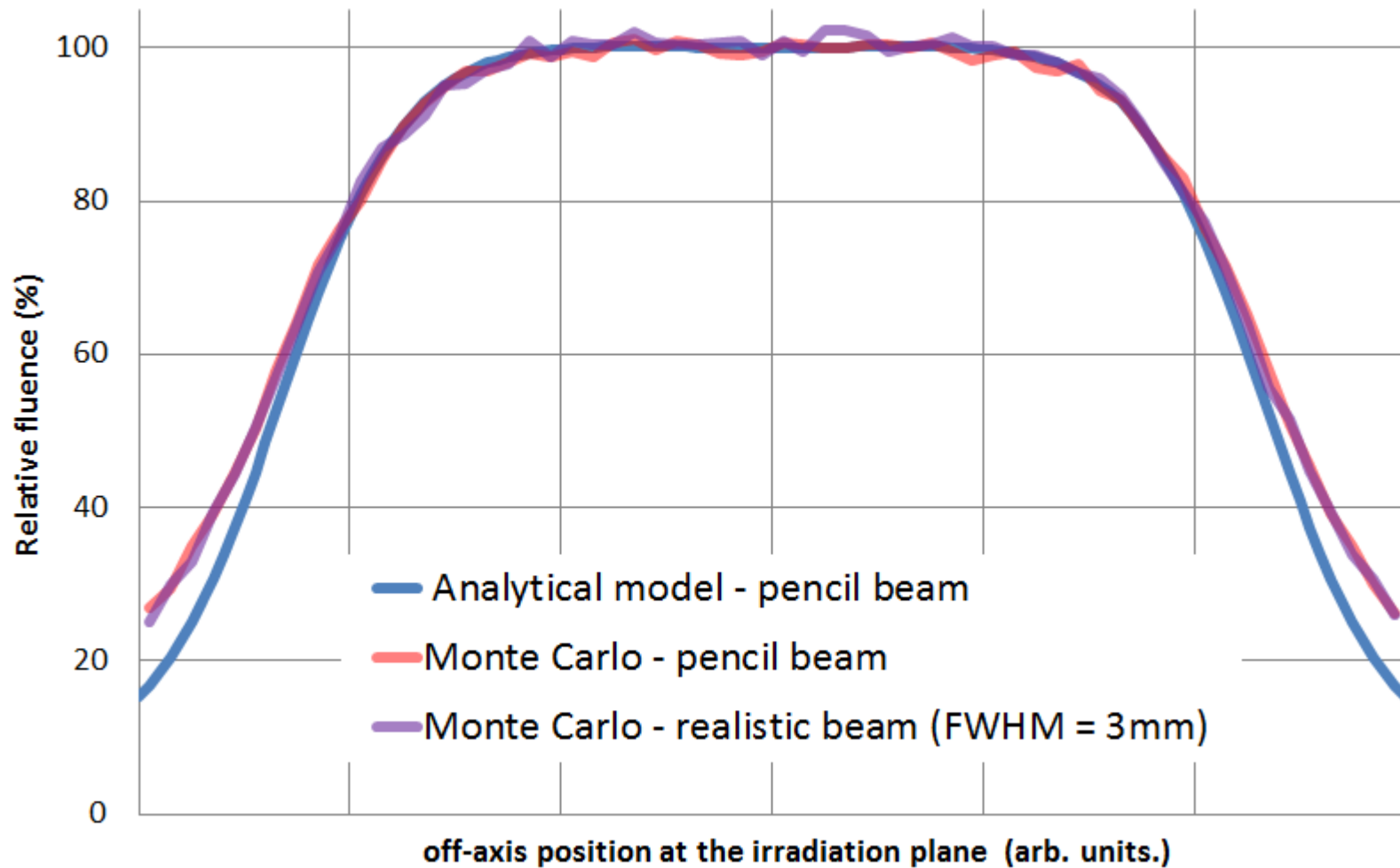
$$\Phi(Z_2, \vec{r}) = \int_0^{2\pi} \int_0^{\rho_{max}} \Phi_1(Z_1, \vec{\rho}) \Phi_2(Z_2, \vec{r}; Z_1, \vec{\rho}) \rho d\rho d\varphi$$

Numerical integration is straight forward



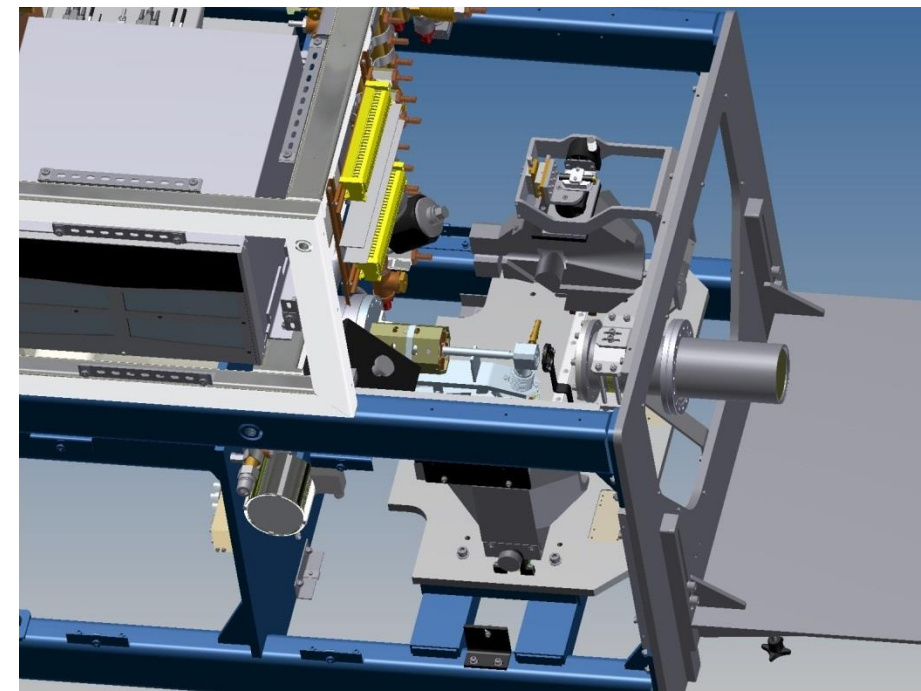
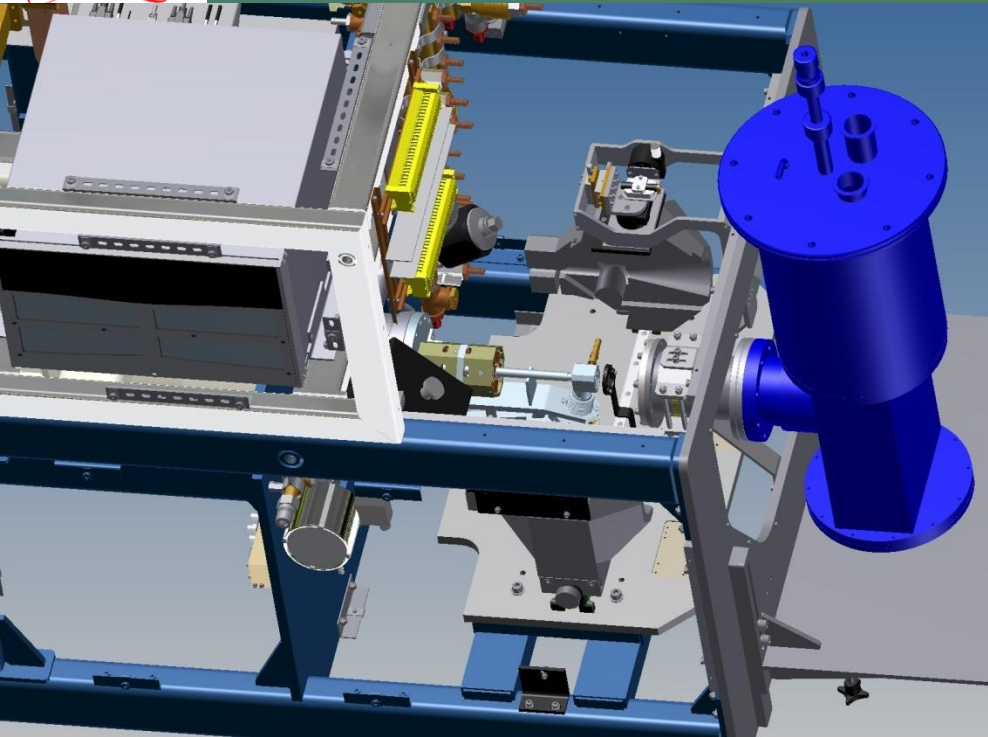


# Calculation of electron fluence – simple model





# Influence of the applicator on the electron distribution at the irradiation plane

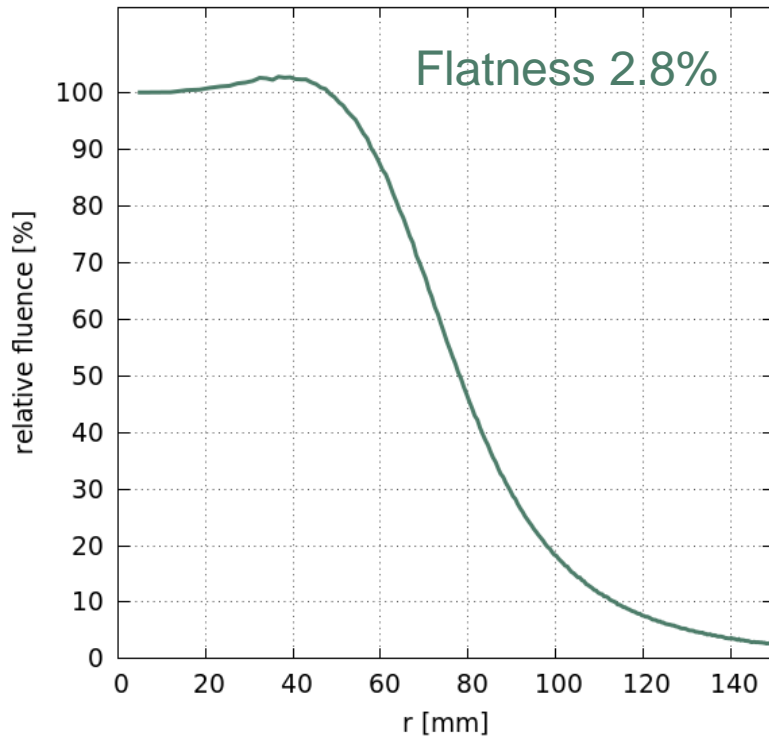




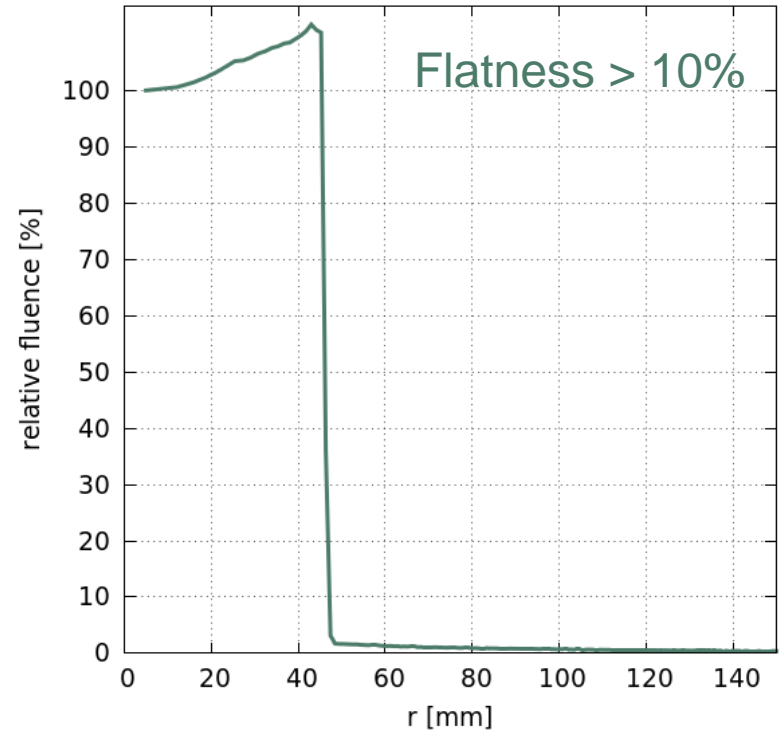
# Influence of the applicator on the electron distribution at the irradiation plane

The same scattering and flattening foils (MC calculation)

Without an applicator



With  $\Phi 93$  mm circular applicator

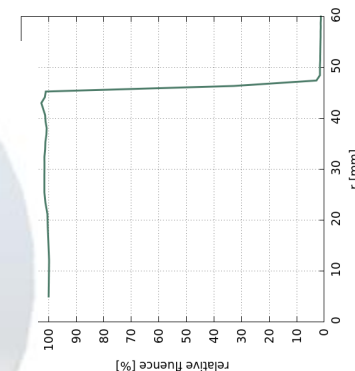
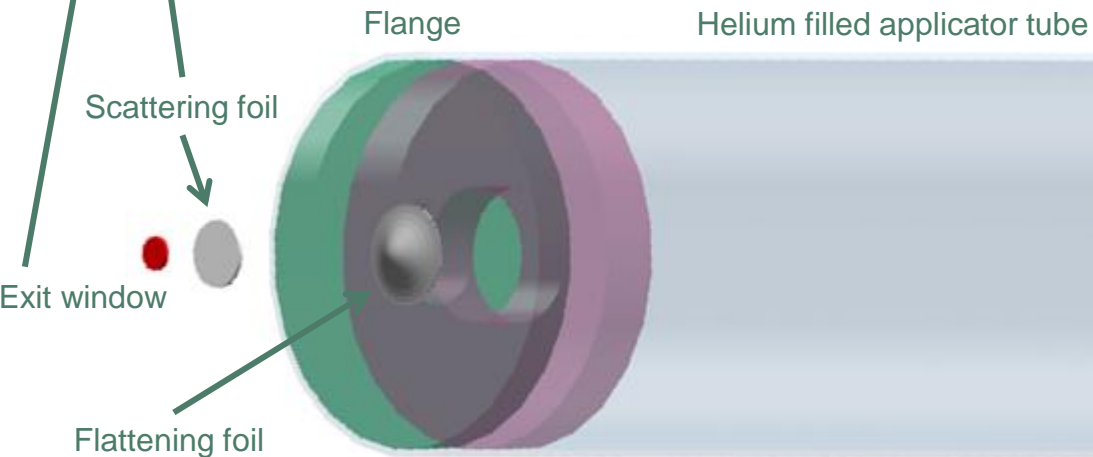
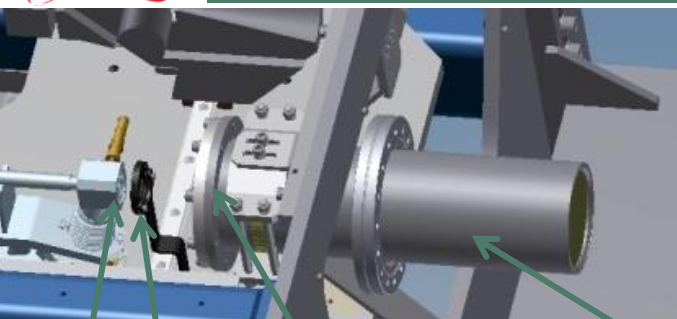


Flatness calculated within  $\Phi 82$  mm field

Setup: exit window Ti 0.05 mm, 20 mm Air, scattering foil Ta 0.03 mm, 60 mm Air, flattening foil Al H=1mm, R=5.5 mm, SSD=400 mm



# Tools for designing optimal foils – Geant4 model



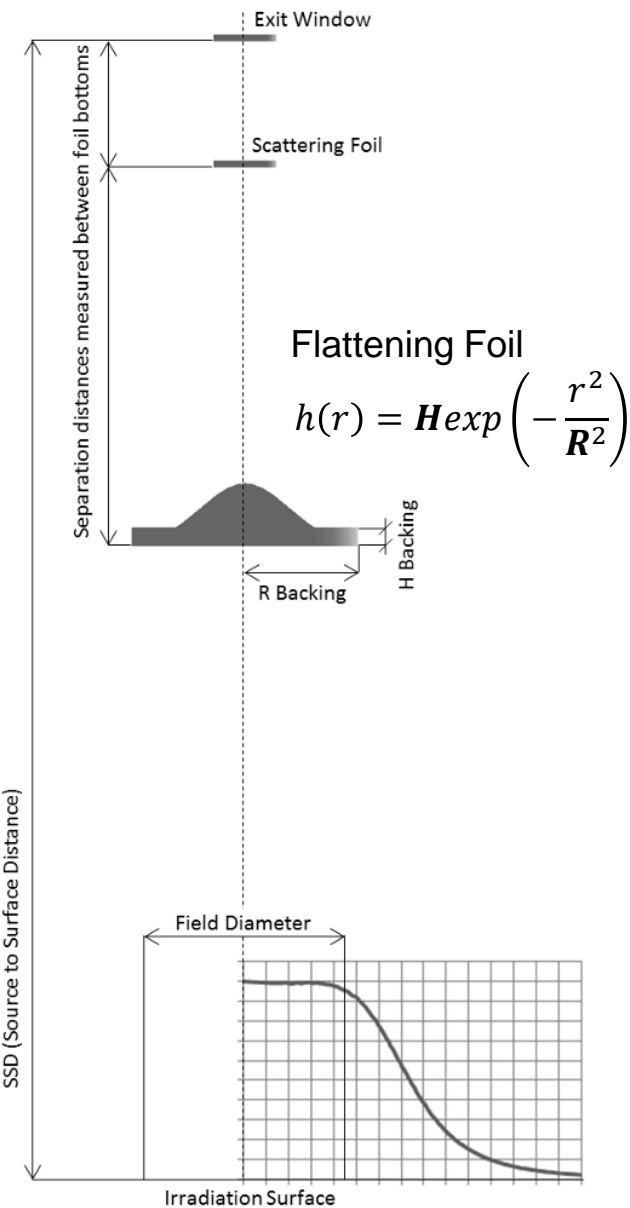
Electron fluence and energy are histogrammed at the end of the applicator.

Flatness of the fluence distribution is calculated within the field as

$$flatness = \left( \frac{\Phi_{max}}{\Phi_{min}} - 1 \right) \cdot 100\%$$



# Dual-foil system: degrees of freedom

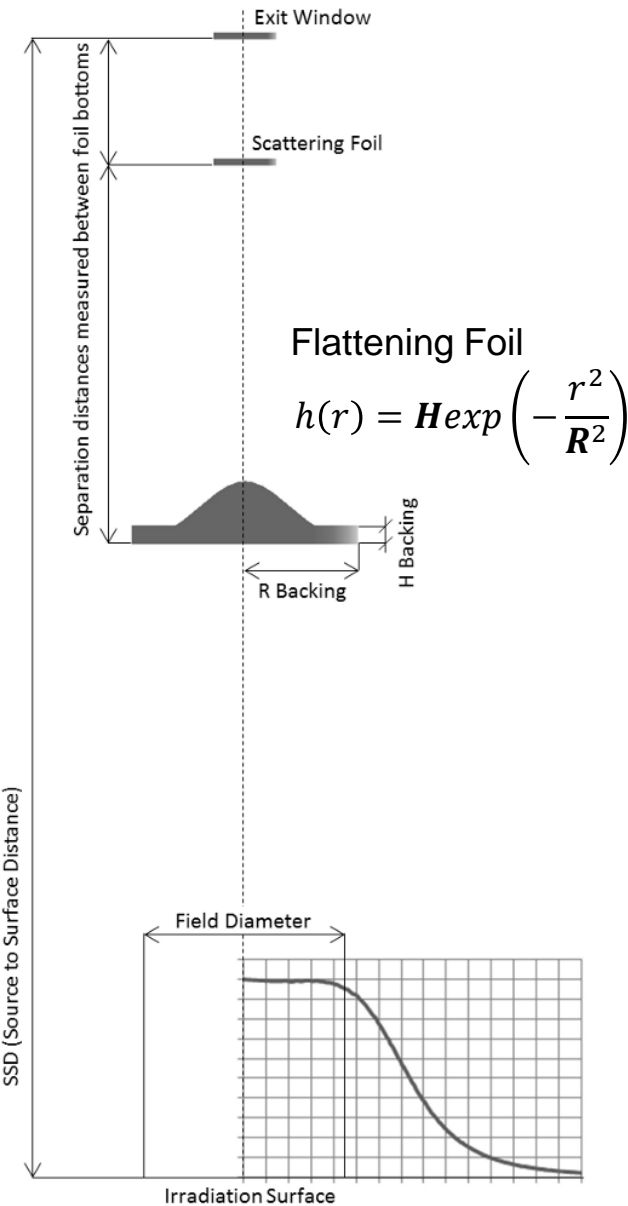


Parameters of the system:

- Beam energy – fixed at 9 MeV
- Irradiation field size – fixed at  $\Phi$  82 mm
- SSD – fixed at 400 mm
- Scattering foil position – ?
- Scattering foil material – ?
- Scattering foil thickness – ?
- Flattening foil material – ?
- Flattening foil position – ?
- Flattening foil thickness and width – ?



# Dual-foil system: degrees of freedom



Parameters of the system:

- Beam energy – fixed at 9 MeV
- Irradiation field size – fixed at  $\Phi$  82 mm
- SSD – fixed at 400 mm
- Scattering foil position – as much upstream as possible – space for air cooling must be provided between the exit window and the scattering foil
- Scattering foil material – ?
- Scattering foil thickness – ?
- Flattening foil material – ?
- Flattening foil position – ?
- Flattening foil thickness and width – ?





# Dual-foil system: Selection of materials

Mass Scattering Power  $\frac{T}{\rho} \sim \frac{Z^2}{A}$

Collisional Stopping Power  $S_{col} \sim \frac{Z}{A}$

## Scattering Foil

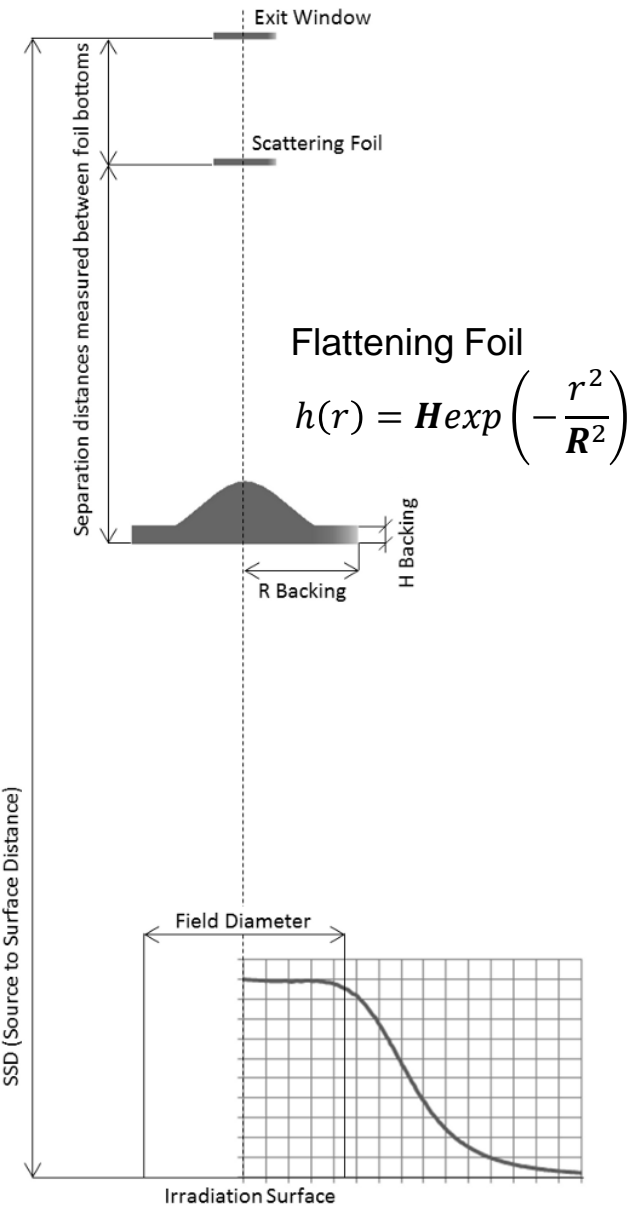
- The higher the Z the better (Bi, Pb, Au)
- High melting point (W, Ta)
- Availability, price (Ta)

## Flattening Foil

- The higher the Z the better (Bi, Pb, Au)
- Feasible to machine a profiled shape (Al)



# Dual-foil system: degrees of freedom



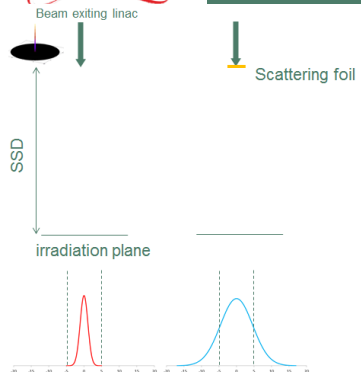
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- Scattering foil material – Ta
- Scattering foil thickness – ?
- Flattening foil material – Al
- Flattening foil position – ?
- Flattening foil thickness and width – ?



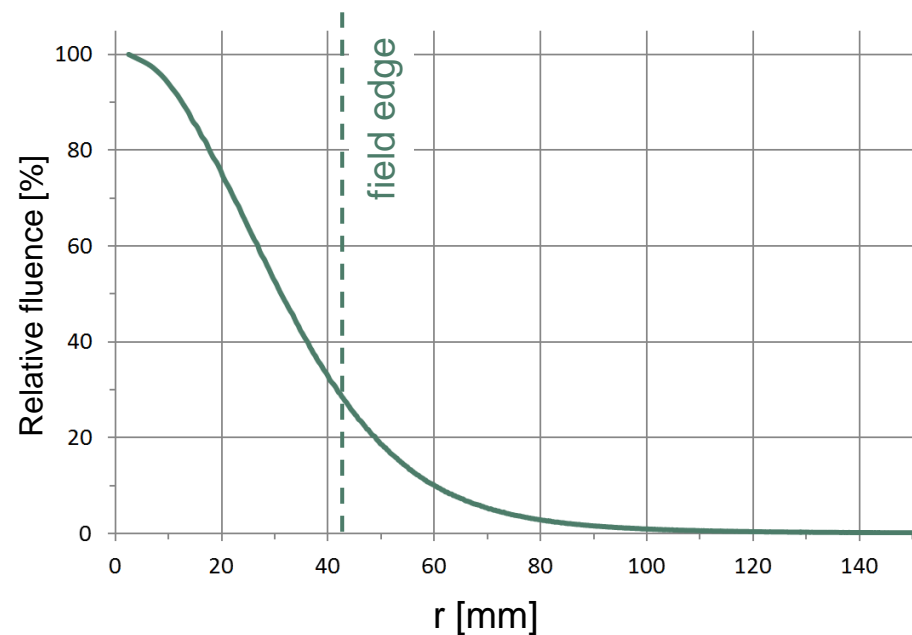


# Dual-foil system: scattering foil thickness

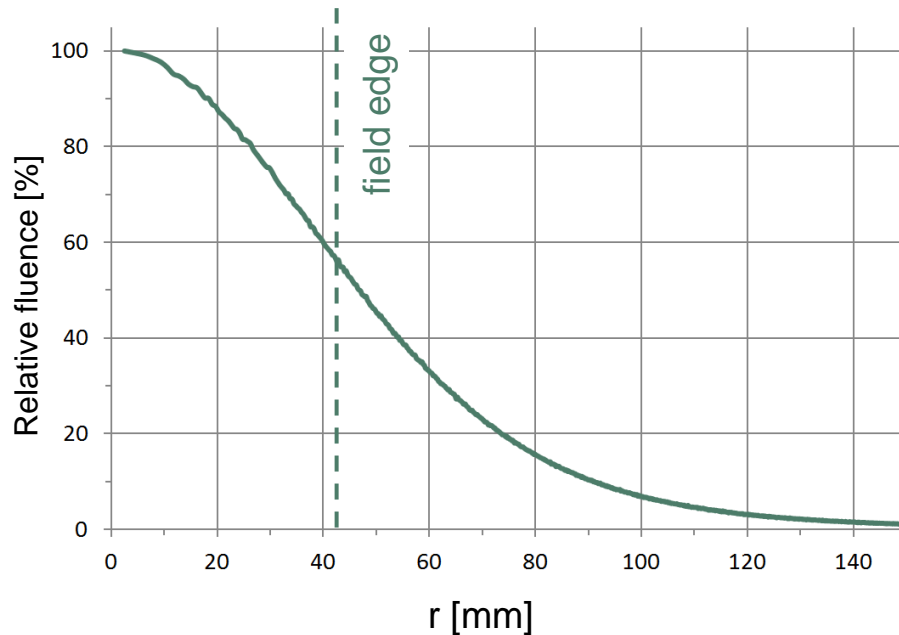


Thumb rule: total thickness of foils is minimal when the first foil thickness is such that, without the second foil, the fluence at the edge of the proposed irradiation field at SSD would be about 60% of the fluence on axis.

Ta 0.01 mm



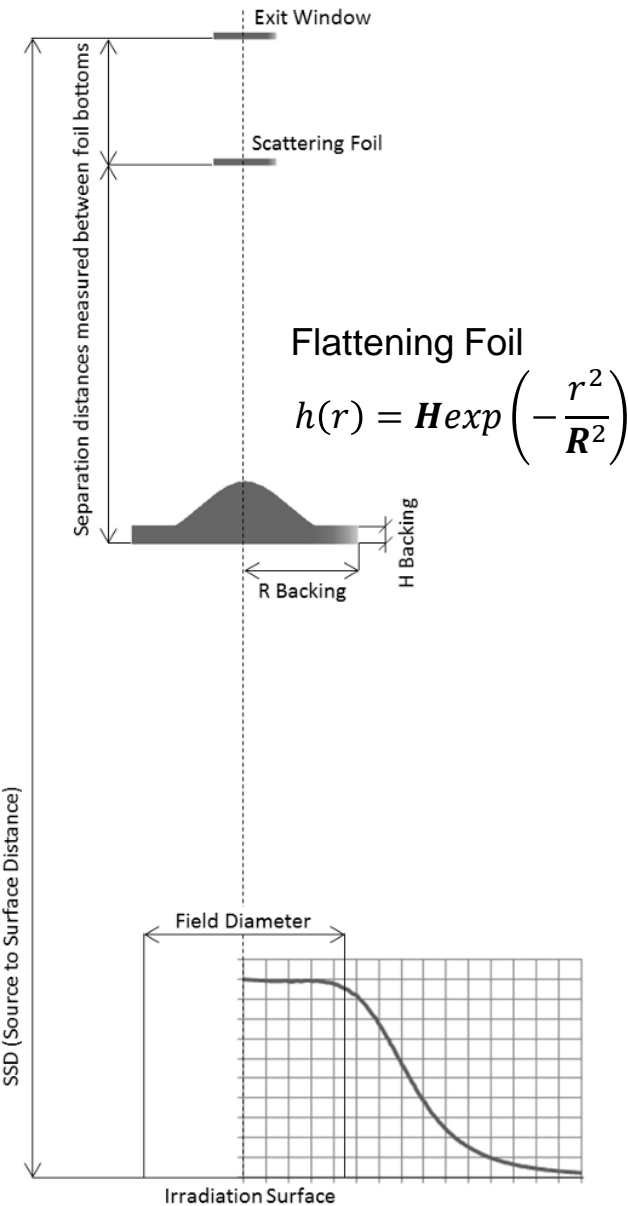
Ta 0.03 mm



- Minimal total energy degradation



# Dual-foil system: degrees of freedom



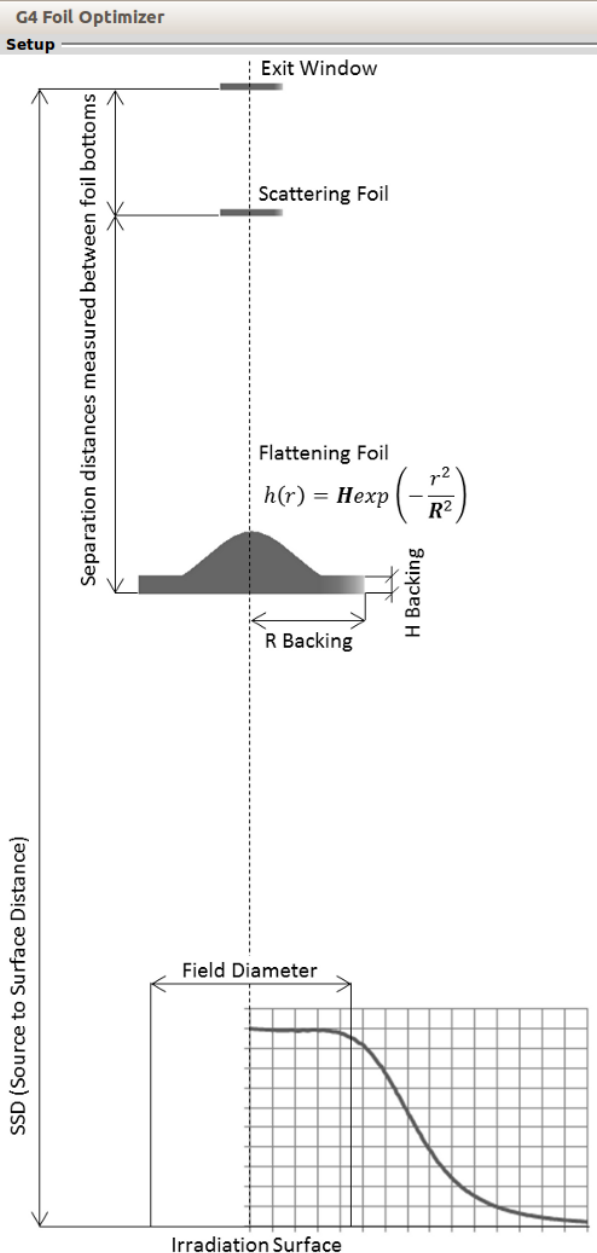
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- SSD – fixed at 400 mm
- Scattering foil position – as much upstream as possible – space for air cooling must be provided between the exit window and the scattering foil
- Scattering foil material – Ta
- Scattering foil thickness – 0.03 mm (tentatively)
- Flattening foil material – Al
- Flattening foil position – ?
- Flattening foil thickness and width – ?





# A tool for automatized design optimization



**G4 Foil Optimizer**

**Beam**  
Set beam energy (MeV): 9

**Exit Window**  
Set material: G4\_Ti Set thickness (mm): 0.05

**Exit Window to Scattering Foil Distance**  
Set Exit Window to Scattering Foil separation distance (mm): 20

**Scattering Foil**  
Set material: G4\_Ta Set thickness (mm): 0.03

**Foil separation**  
Set foil separation distance (mm): 60

**Flattening Foil**  
Set material: G4\_Al  
Set H min (mm): 0.5 Set H max (mm): 4 Set H step (mm): 0.1  
Set R min (mm): 1 Set R max (mm): 10 Set R step (mm): 0.25  
Set flattening foil backing height (mm): 0.25  
Set flattening foil backing radius (mm): 12

**SSD Distance**  
Set SSD (mm): 400

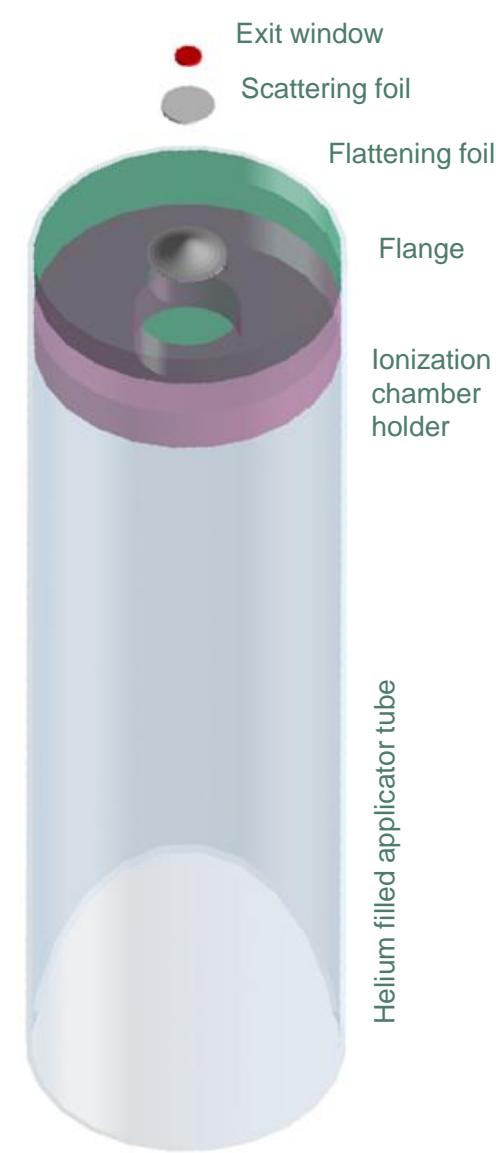
**Fluence histogram**  
Set radius of first bin (mm): 10 Set maximum radius of the histogram (mm): 60

**Field diameter for flatness calculation**  
Set Field Diameter (mm): 82

**Number of events per scan step**  
Set number of events per scan step: 2000000

**SCAN** **EXIT**

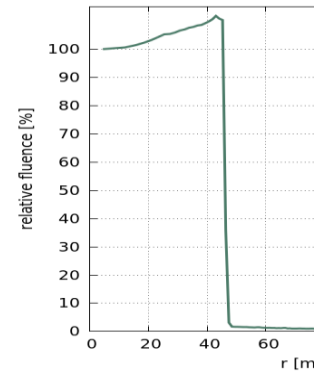
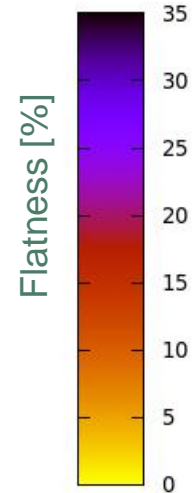
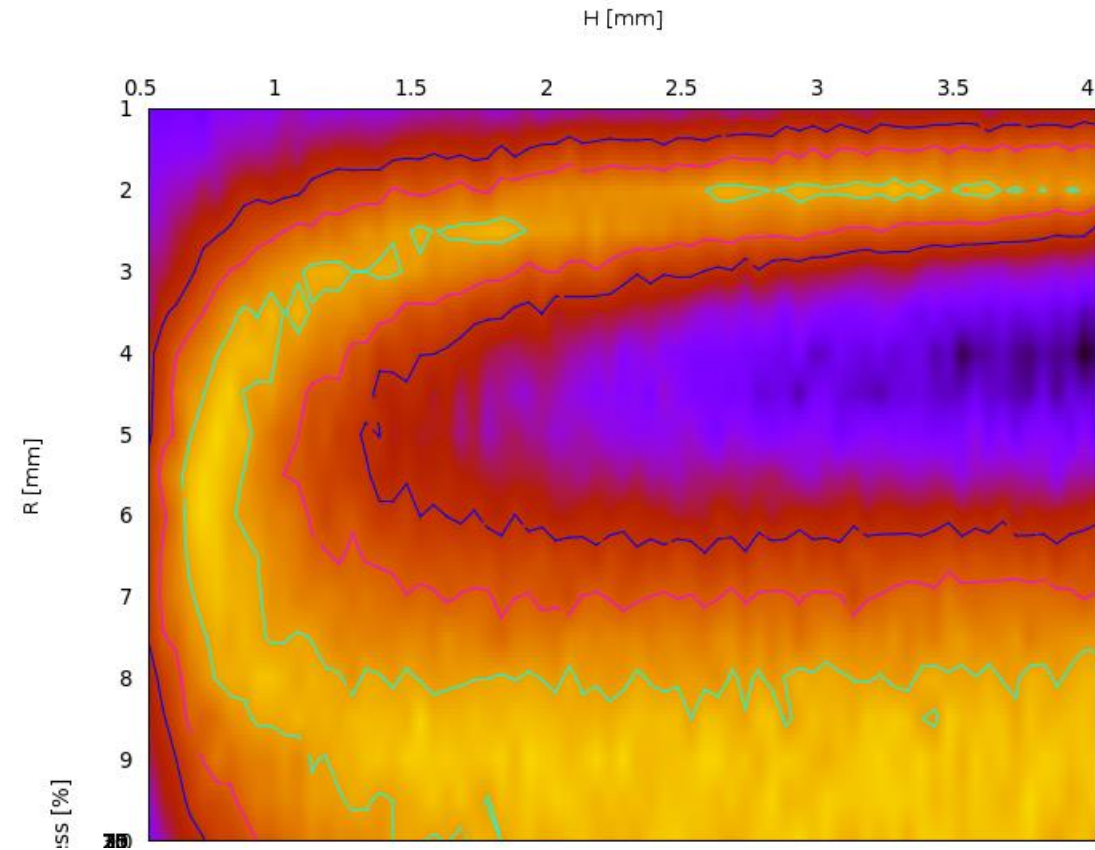
**Explanations**  
All distances should be given in mm and energy in MeV.  
Separation distances are measured between bottom plain of respective foils.  
Bottom plane of the Exit Window is always at Z = 0 mm.  
If a foil or window thickness <= 0 then the respective object is not created in the G4\_DetectorConstruction.  
Position of the Flattening Foil along the Z axis is calculated as a sum of distances between the Exit Window and the Scattering Foil and between the Scattering Foil and the Flattening Foil (even if Scattering Foil does not exist).  
If backing H is set to 0 the flattening foil is created without any backing (pure Gaussian profile). Nonetheless the radial extension of the Flattening Foil is always limited by the Backing Radius parameter, thus it should always be set to a meaningful value.





# Fluence flatness in function of flattening foil parameters

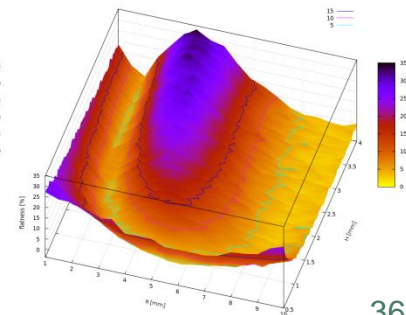
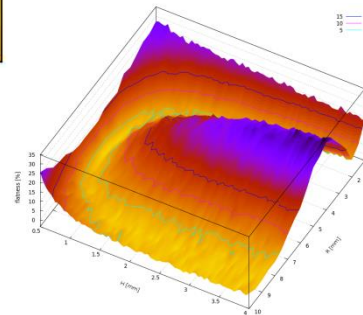
Example of a flatness scan in function of aluminum flattening foil parameters H and R (at fixed scattering foil and separation distances)



$$flatness = \left( \frac{\Phi_{max}}{\Phi_{min}} - 1 \right) \cdot 100\%$$

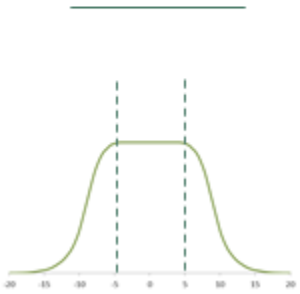
Profile of the flattening foil is:

$$h(r) = H \exp\left(-\frac{r^2}{R^2}\right)$$

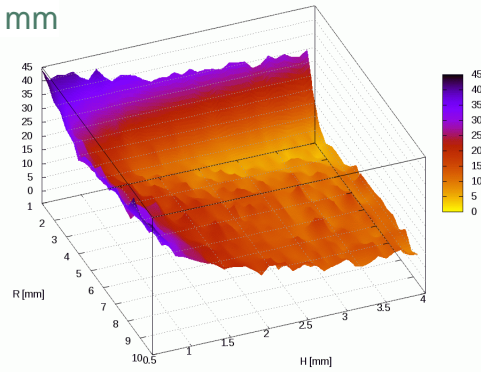




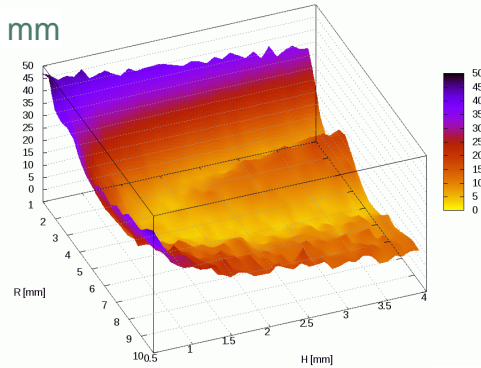
# Dual-foil system: foil separation



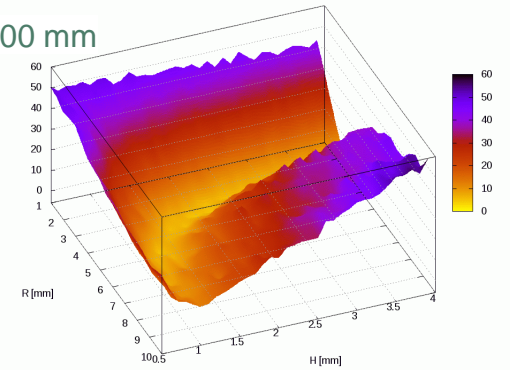
20 mm



50 mm



100 mm



# *An apology of a humble Jagiellonian University graduate*

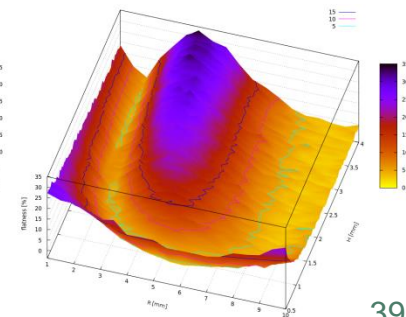
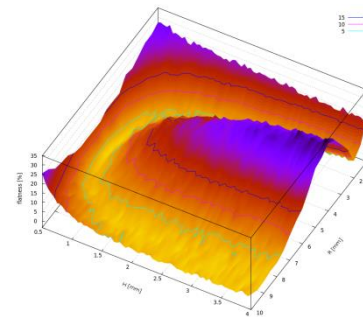
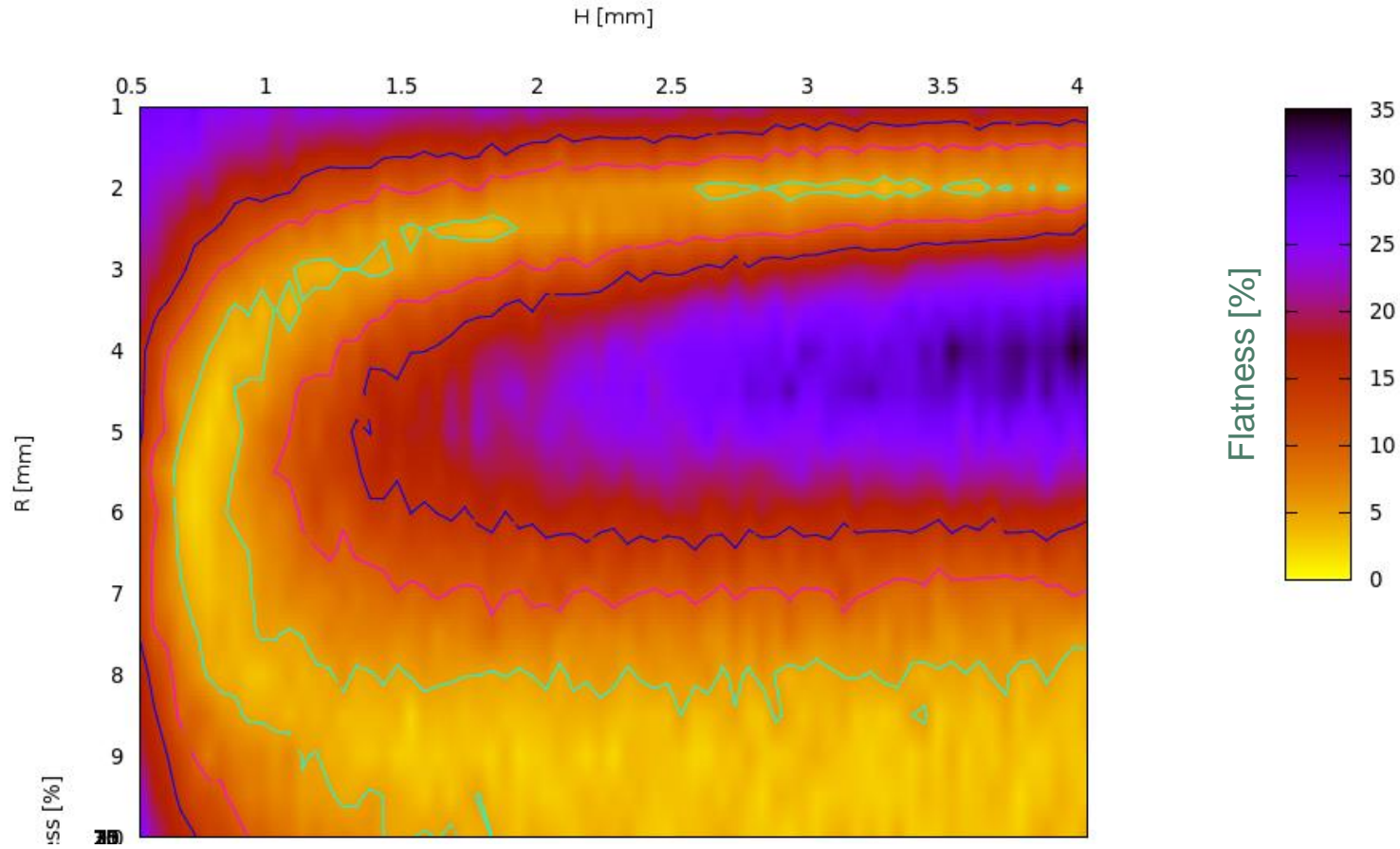


Let reason prevail over force

Assembly Hall of the Collegium Maius, Jagiellonian University, Kraków



# Optimization of the Al flattening foil for the 0.03 mm Ta scattering foil

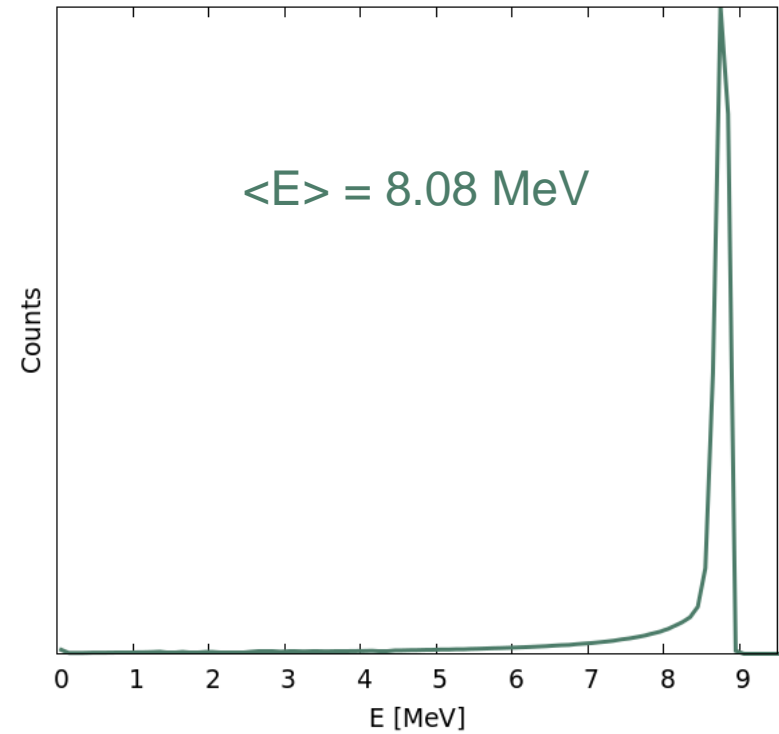
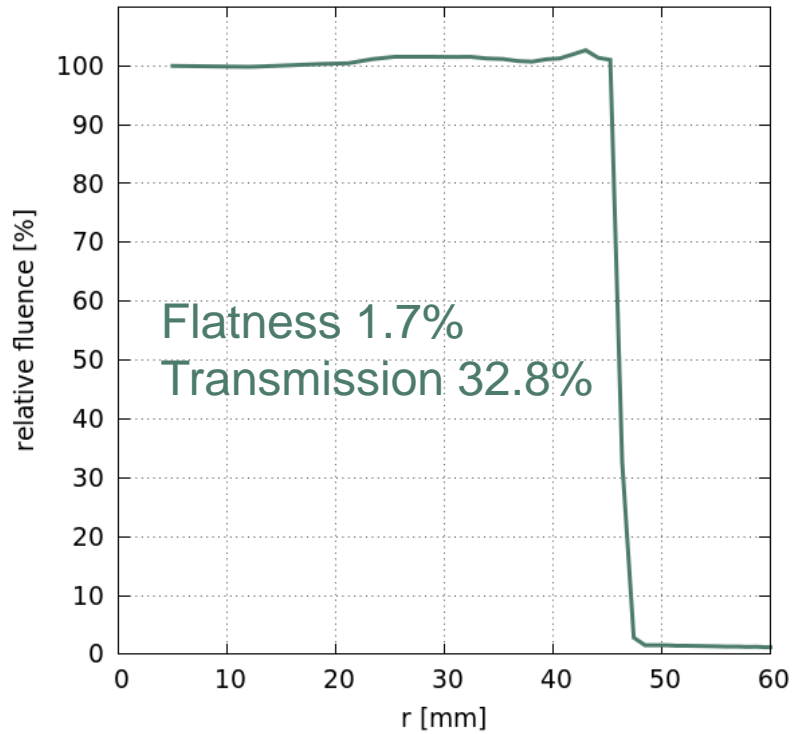




# Optimal Al flattening foil for the 0.03 mm Ta scattering foil

$R = 5.5 \text{ mm}$   
 $H = 0.75 \text{ mm}$

$$h(r) = H \exp\left(-\frac{r^2}{R^2}\right)$$

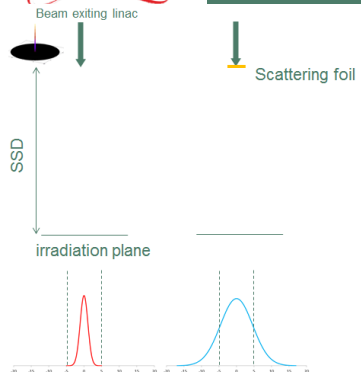


For comparison in the setup without the applicator  
Transmission 24.5%  
 $\langle E \rangle = 8.48 \text{ MeV}$



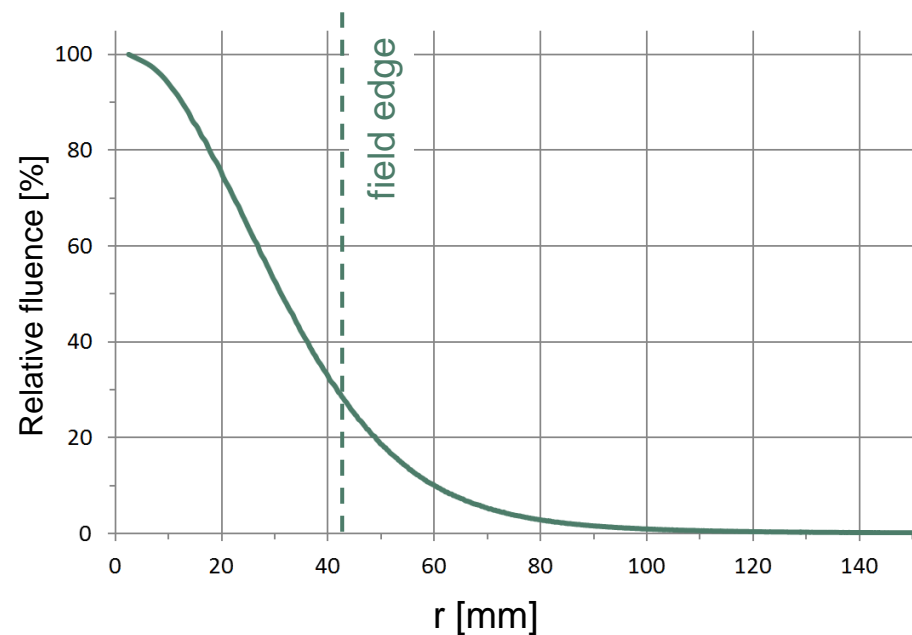


# Dual-foil system: scattering foil thickness

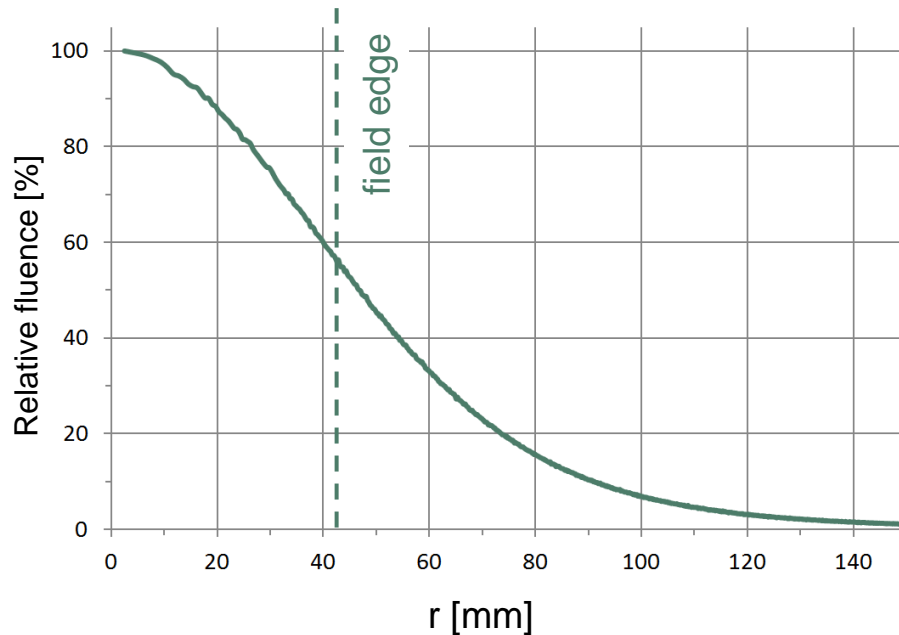


Thumb rule: total thickness of foils is minimal when the first foil thickness is such that, without the second foil, the fluence at the edge of the proposed irradiation field at SSD would be about 60% of the fluence on axis.

Ta 0.01 mm



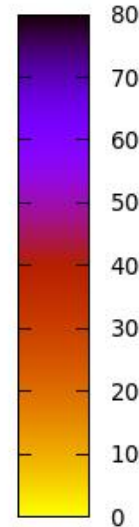
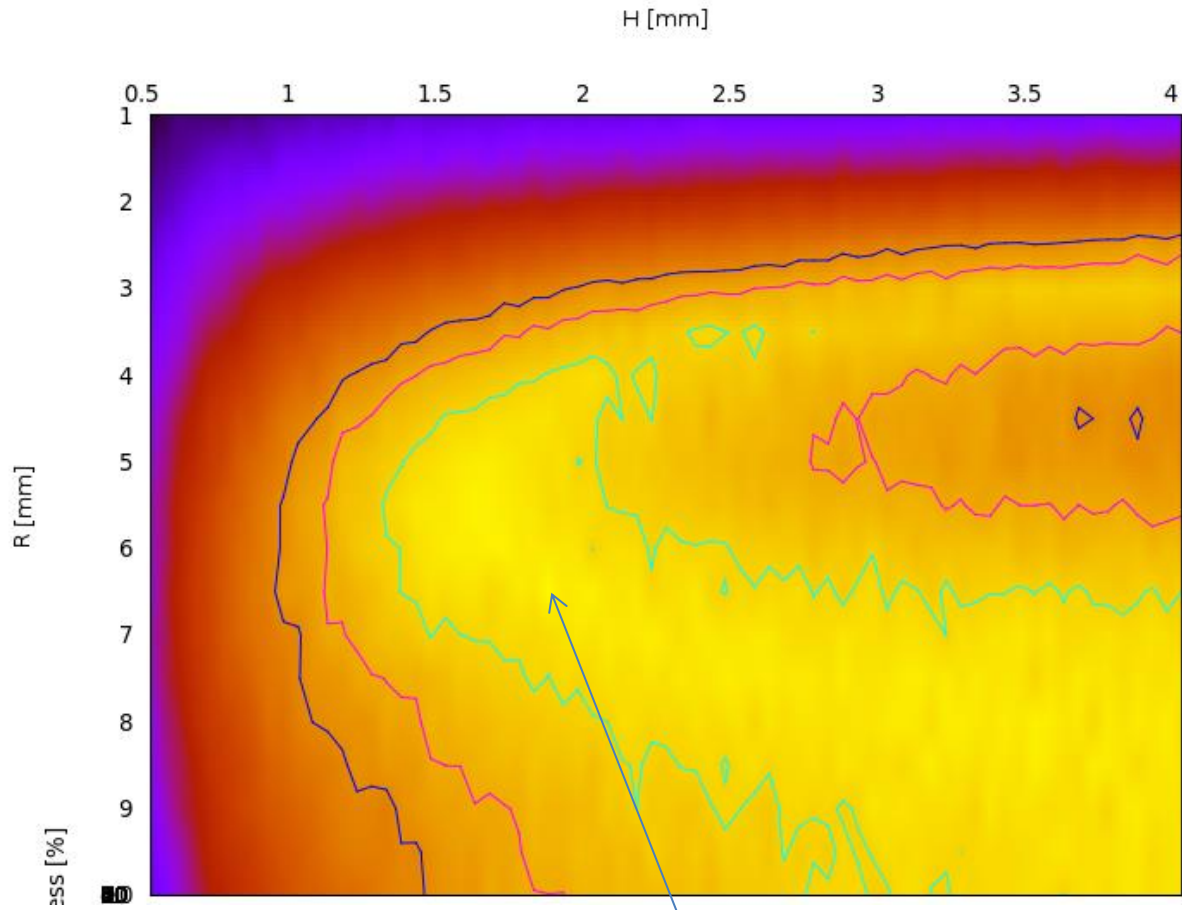
Ta 0.03 mm



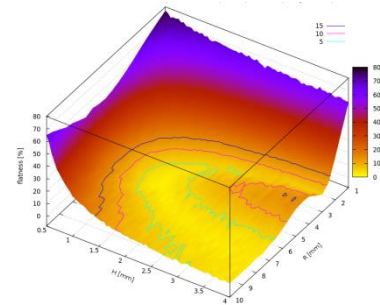
- Minimal total energy degradation



# Optimization of the Al flattening foil for the 0.01 mm Ta scattering foil.



minimum





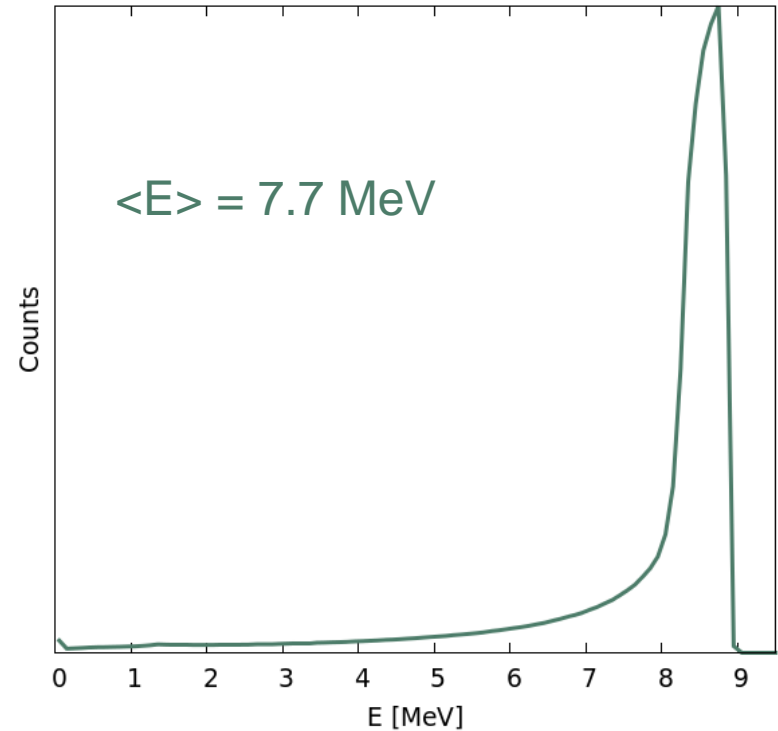
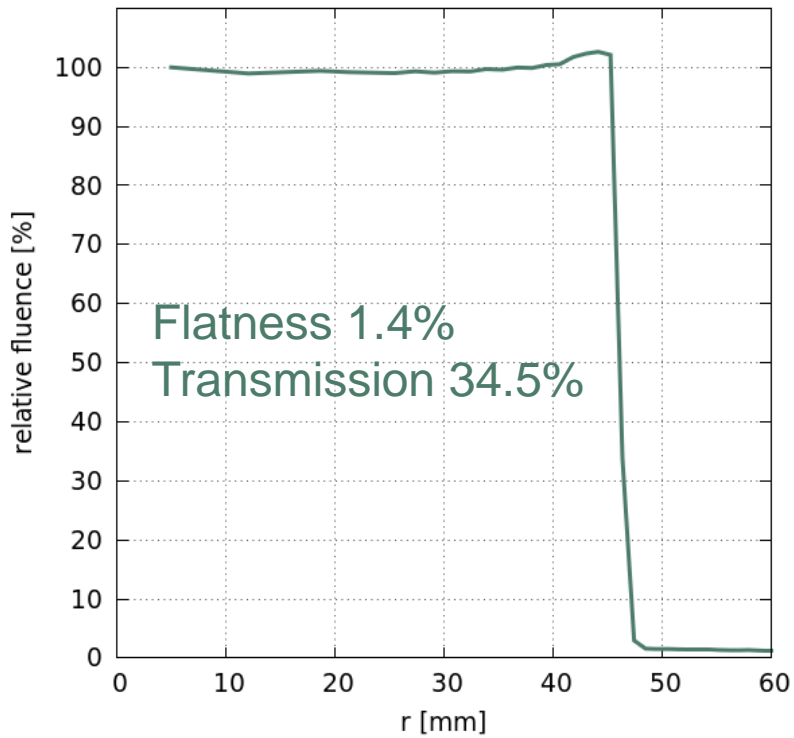
# Al flattening foil for the 0.01 mm Ta scattering foil – optimal flatness

Minimal flatness

R=6.5 mm

H=1.85 mm

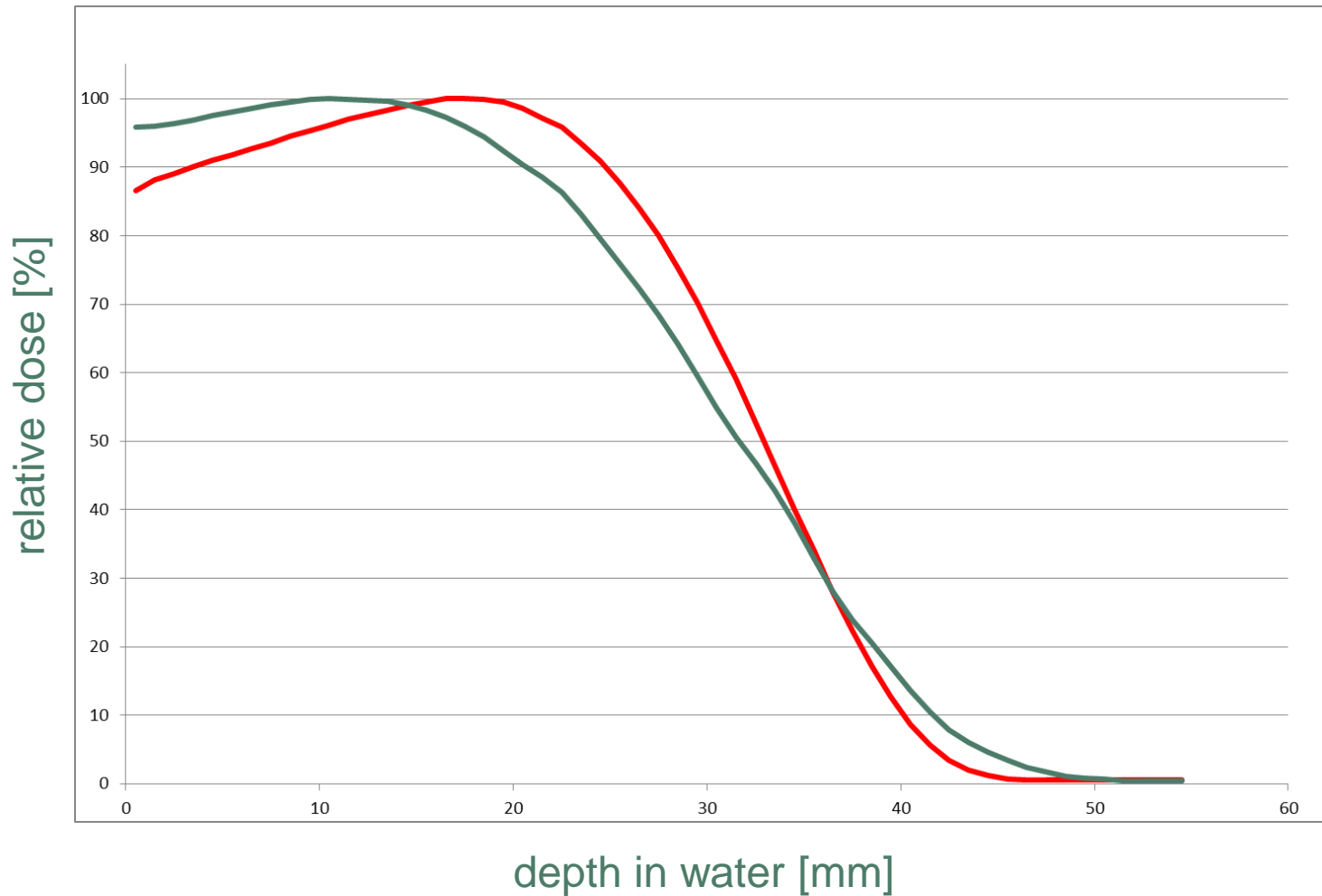
$$h(r) = H \exp\left(-\frac{r^2}{R^2}\right)$$





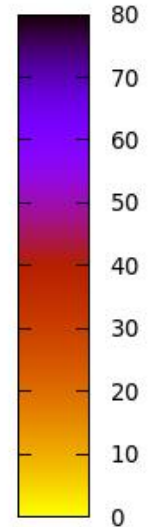
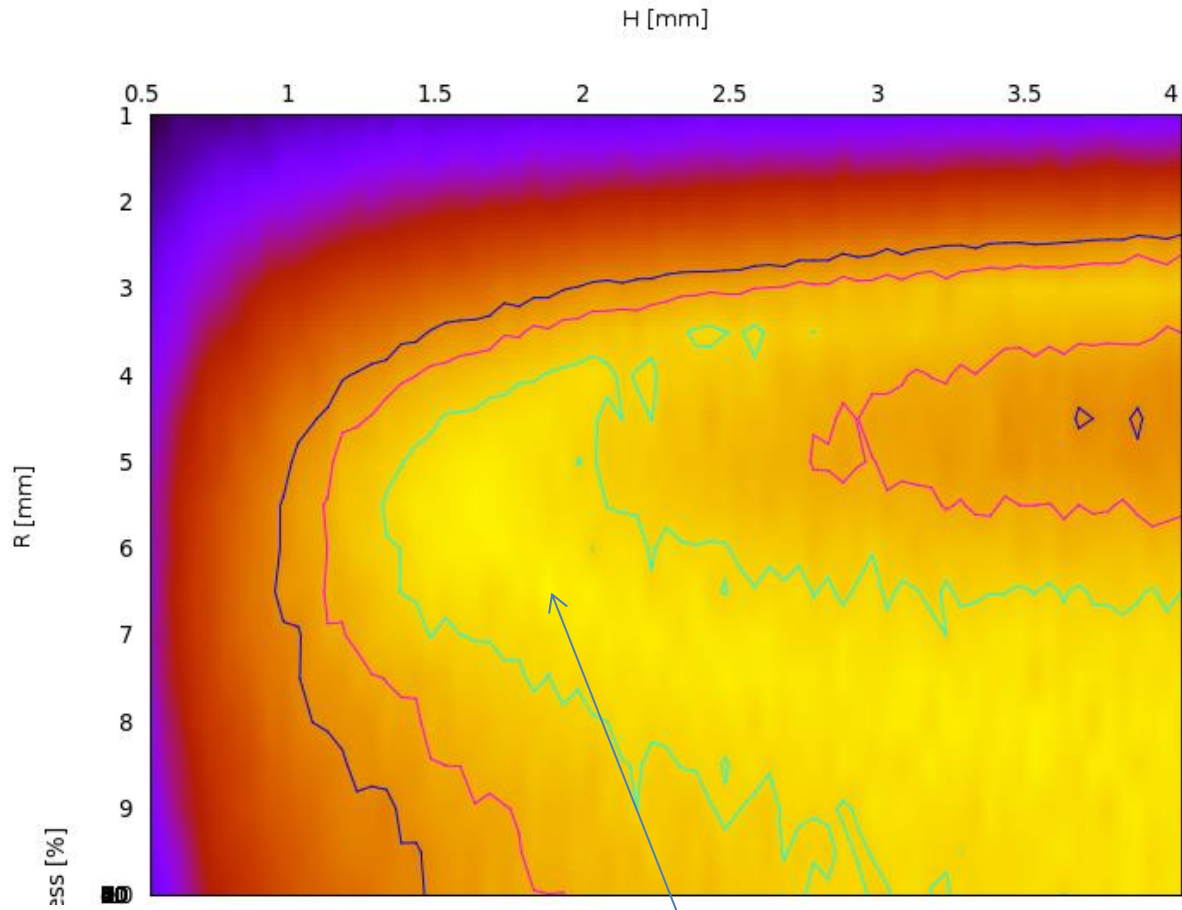
# Depth Dose

„less degraded” VS „more degraded” energy spectrum

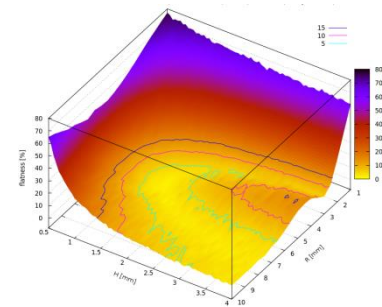




# Optimization of the Al flattening foil for the 0.01 mm Ta scattering foil.



minimum

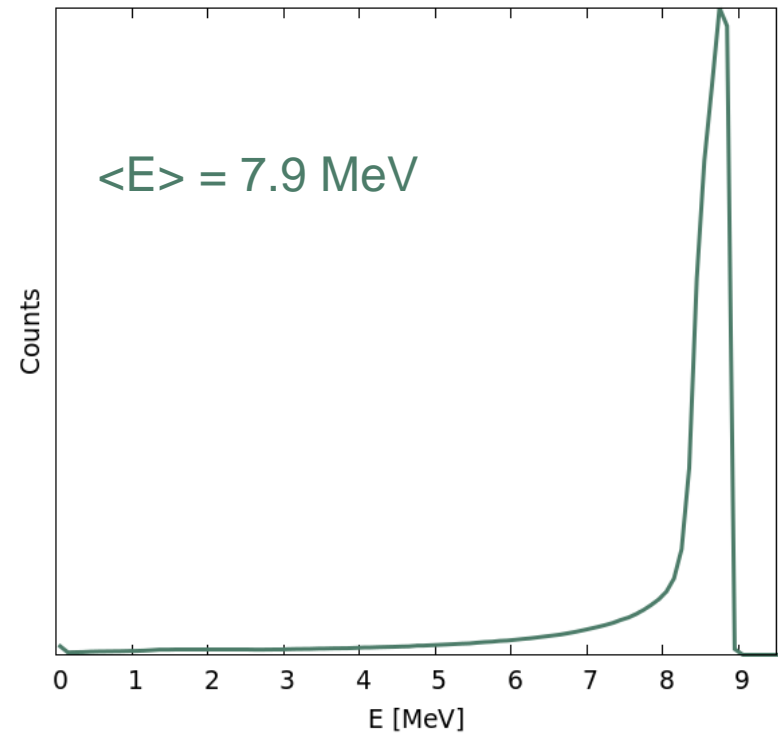
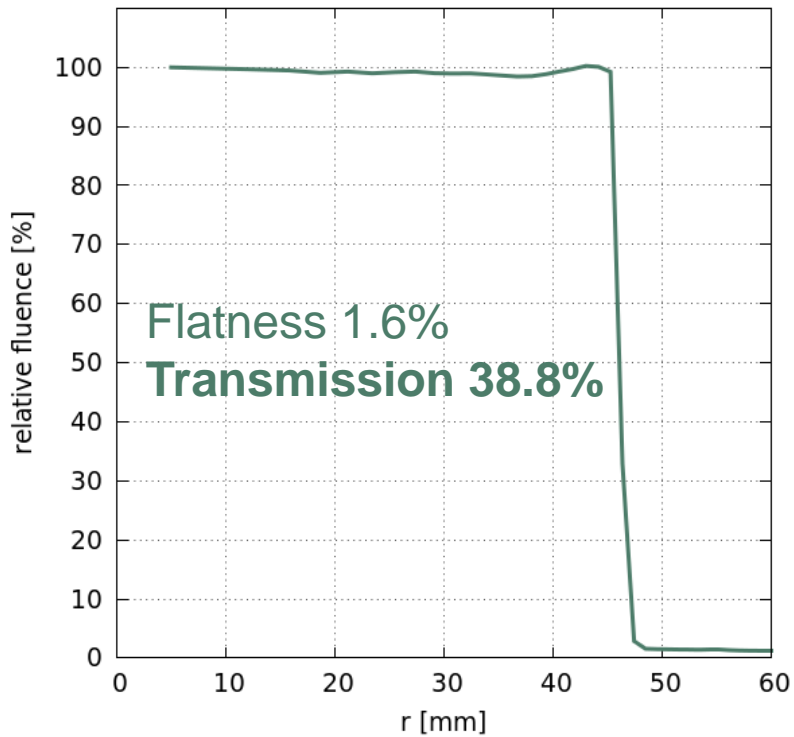




# Al flattening foil for the 0.01 mm Ta scattering foil – optimal transmission

R=6 mm  
H=1.5 mm

$$h(r) = H \exp\left(-\frac{r^2}{R^2}\right)$$



Selected for production



# Dose rate estimation (conservative)

Transmission to the irradiation plane 39%  
Initial beam current  $I_{imp} = 50 \text{ mA/imp}$  (max 100 mA)  
Impulse duration  $t_{imp} = 4 \mu\text{s}$   
Repetition frequency = 100 Hz  
Field area =  $\text{Pi} * (4.1)^2 \text{ cm}^2$

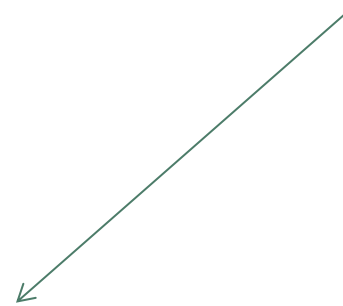
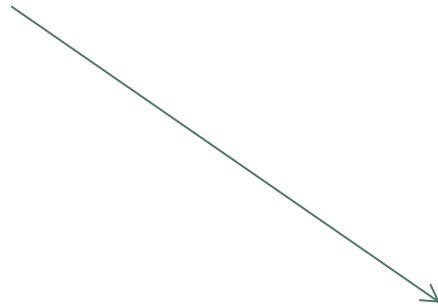


$$\text{Flux} = 9.2 * 10^{11} \text{ electrons/s} * \text{cm}^2$$

$$S_{col} = 1.93 \text{ MeV cm}^2/\text{g} \quad (\text{Air, } E = 7.9 \text{ MeV})$$



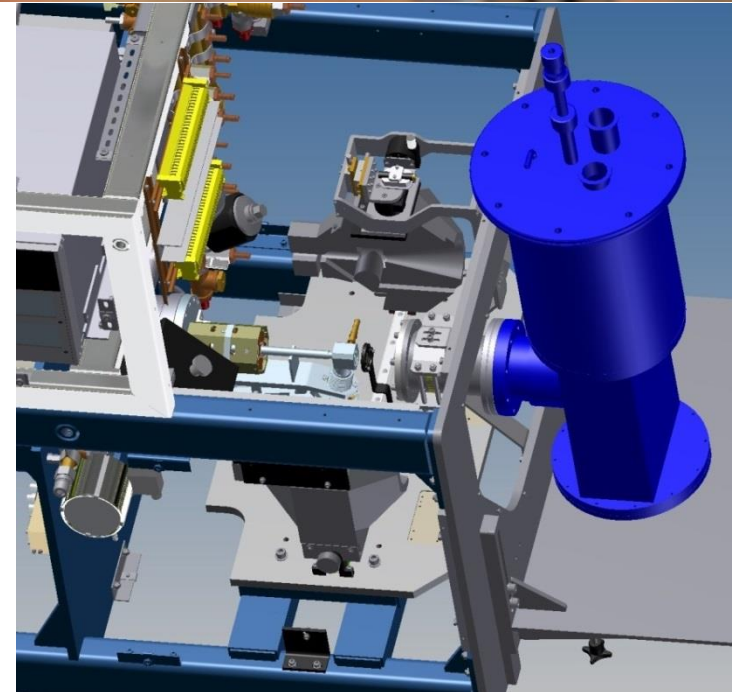
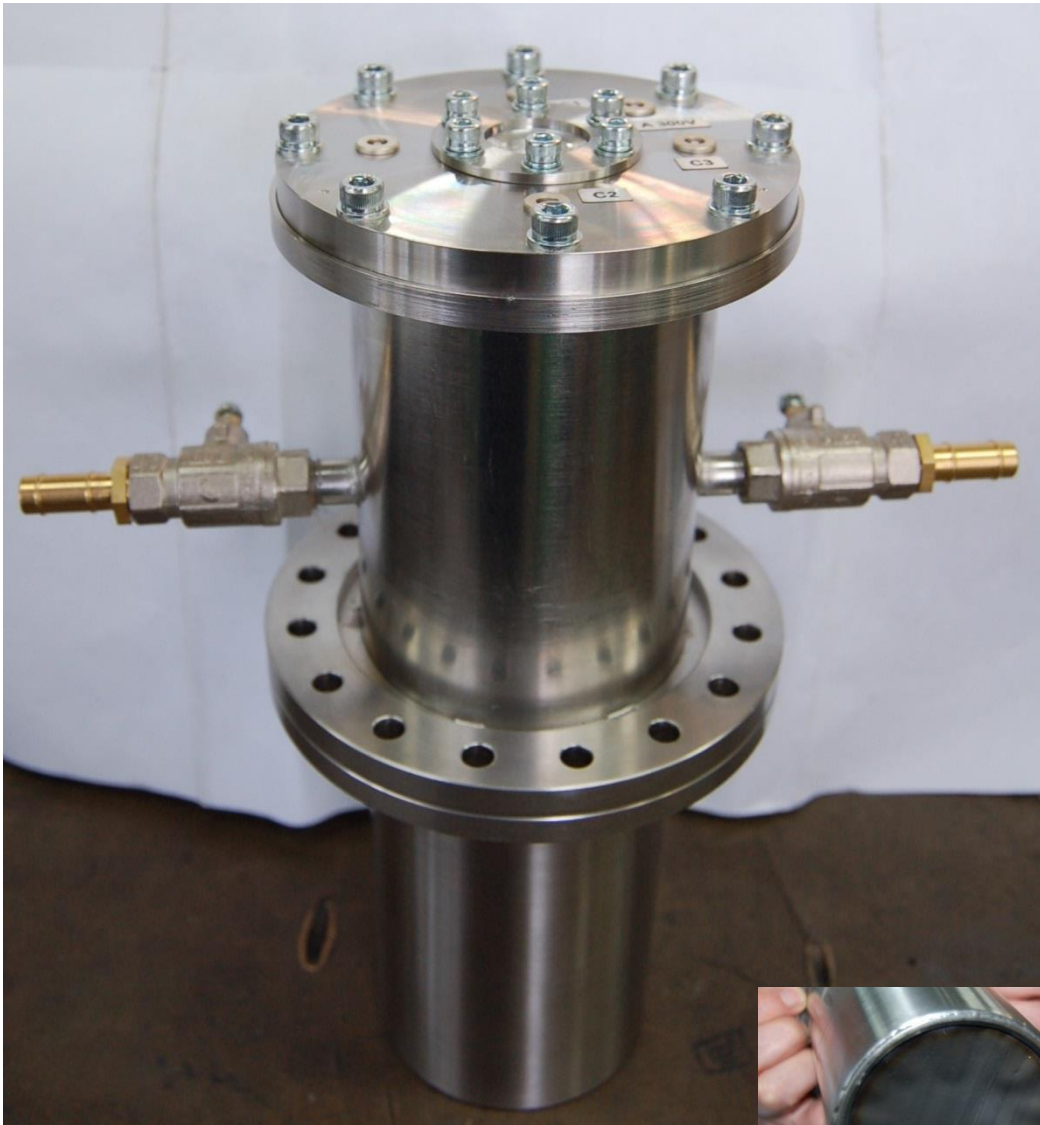
Dose deposited by 1 electron in  $1 \text{ cm}^3$  of air:  
 $D = E/m = 3.09 * 10^{-10} \text{ Gy}$



$$\dot{D} = 284 \text{ Gy/s} = 17 \text{ kGy/min} = 1 \text{ MGy/h}$$



# Current state







# Conclusions

- Passive forming could be equally efficient as scanning
- Dare to question known rules (of thumb)
- Dedicated Geant4 application with automation facility for rapid system development
- Optimum setup found via „brute force” multidimensional Monte Carlo optimization study
- Expected  $\dot{D} = 284 \text{ Gy/s} = 17 \text{ kGy/min} = 1 \text{ MGy/h}$  (at  $\sim \Phi 80\text{mm}$  field)
- Most of the system components already fabricated at NCBJ
- Delivery, installation and tests at NTL@WPT expected in the second half of 2015



*Thank you for your attention!*